



*The Abdus Salam*  
**International Centre for Theoretical Physics**



SMR/1758-6

**"Workshop on Ion Beam Studies of Nanomaterials:  
Synthesis, Modification and Characterization"**

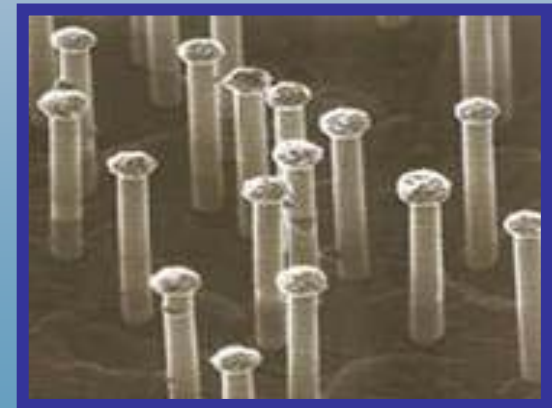
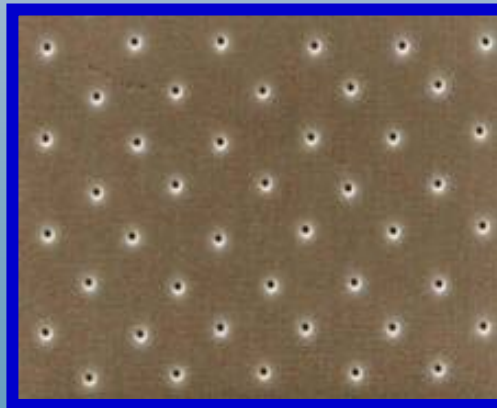
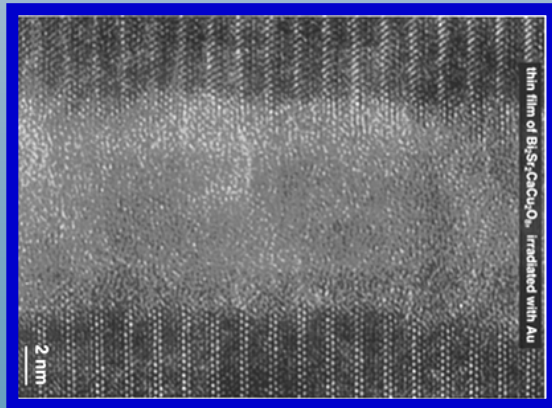
**26 June - 1 July 2006**

**Material Modifications & Nanoscience  
with MeV-GeV ions**

*Christina Trautmann  
Gesellschaft fuer Schwerionenforschung GmbH  
Darmstadt, Germany*

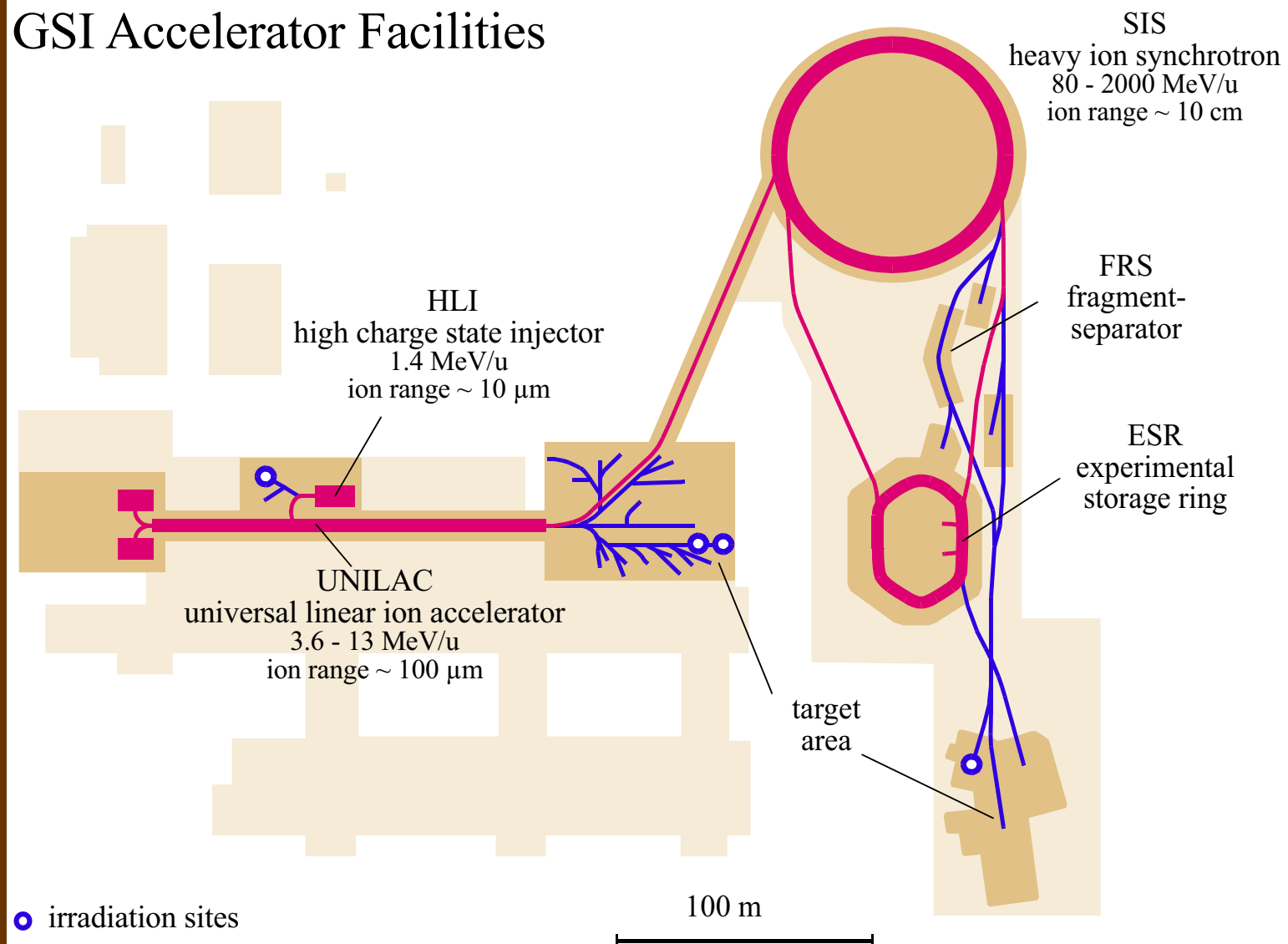
# Material modifications and nanoscience with MeV-GeV ions

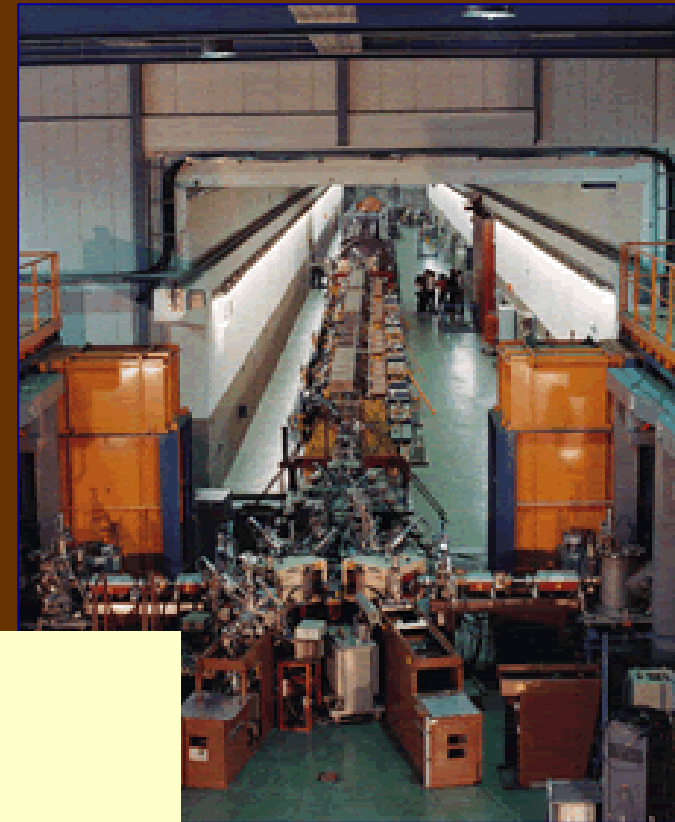
- Track formation with MeV-GeV ions
- Applications: ion track membranes  
nanowires  
single nanopores



# Accelerator facility for MeV – GeV ion beams

## GSI Accelerator Facilities





## Heavy ion accelerator facilities for materials science

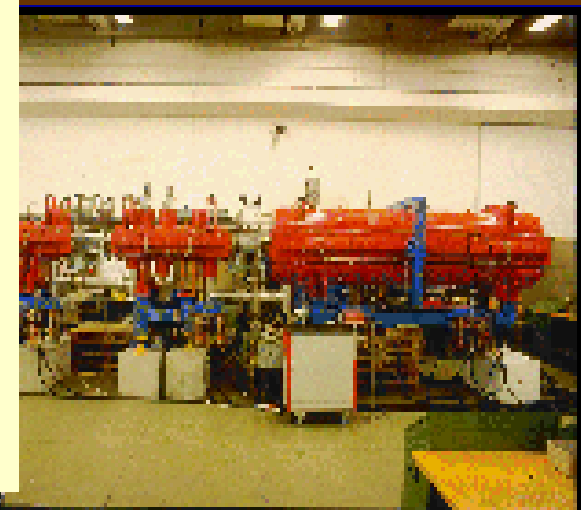
|               |                      |                      |
|---------------|----------------------|----------------------|
| 10-1000 MeV/u | linear & synchrotron | Darmstadt (Ger)      |
| 1-100 MeV/u   | cyclotron            | Ganil, Caen (F)      |
| 25 MeV/u      | cyclotron            | Dubna (Ru)           |
| 5 MeV/u       | cyclotron            | Berlin (Ger)         |
| 1-30 MeV/u    | cyclotron            | Louvain La Neuve (B) |

China: Lanzhou

India: Nuclear Science Center Delhi

Japan: Tokai, Riken, Takasaki, Chiba

USA: AGS -Brookhaven, Argonne Nat. Lab

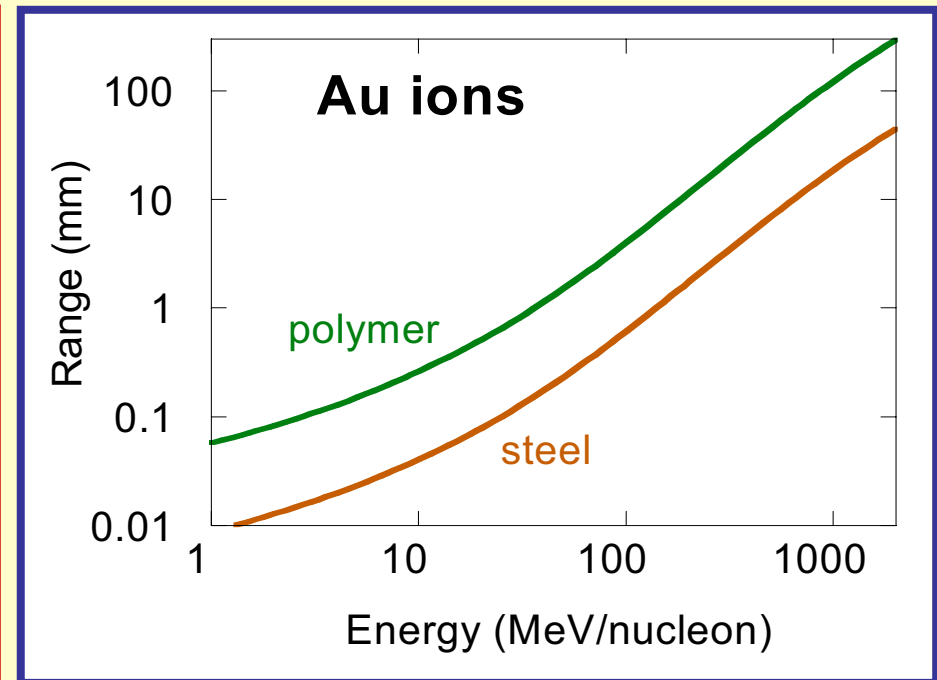
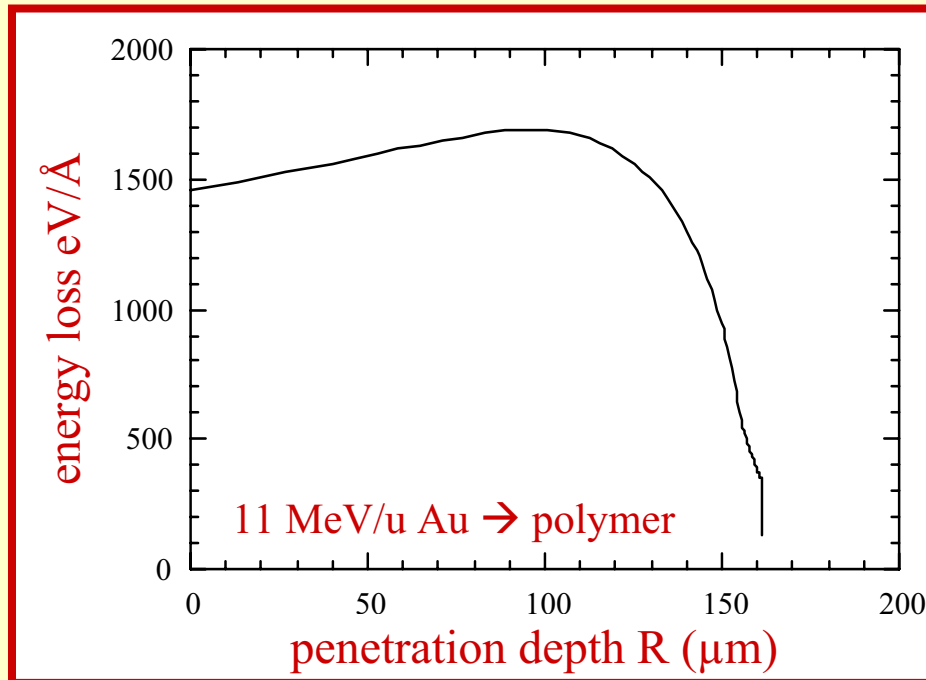


# ion range versus beam energy



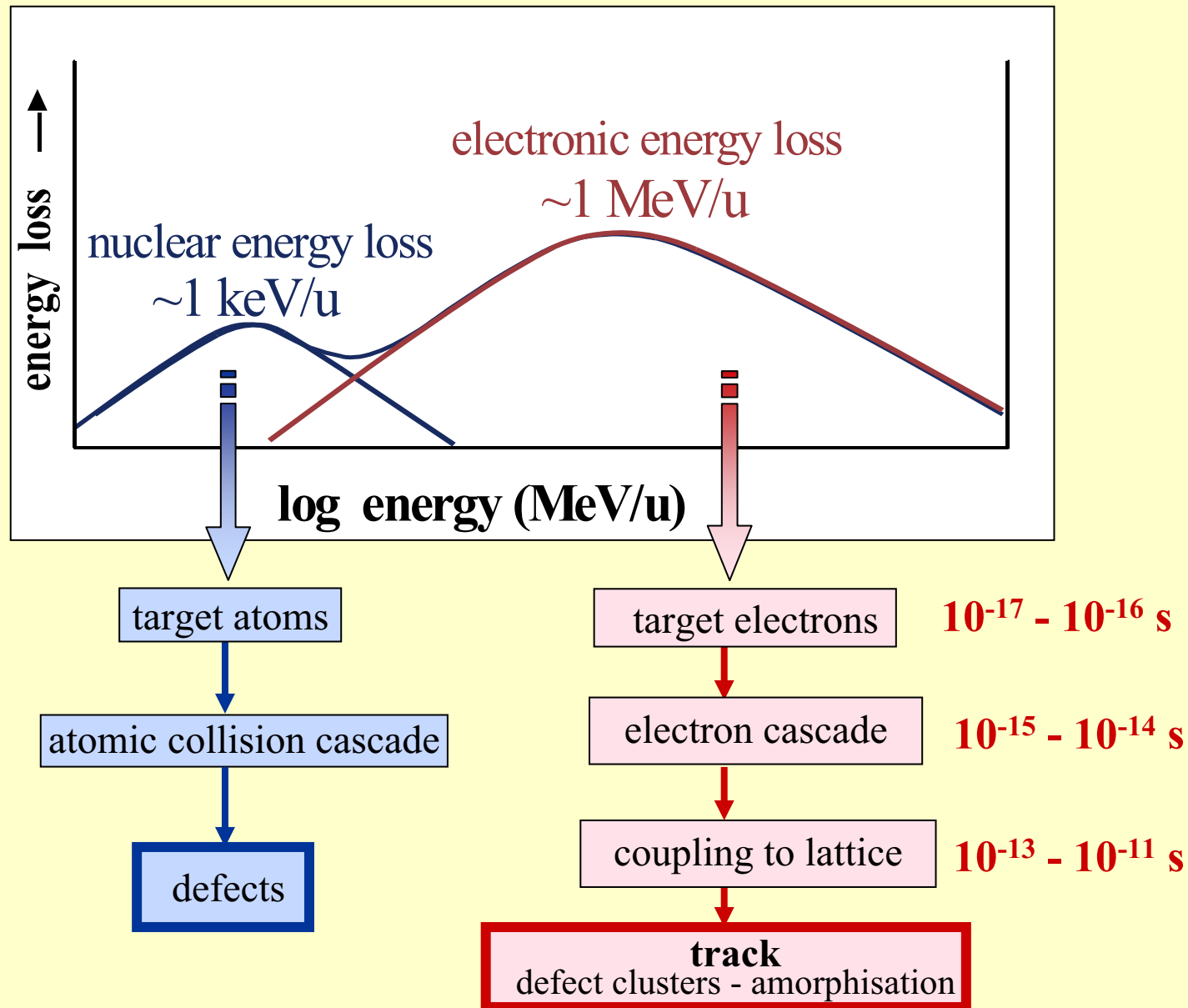
energy loss versus depth

$$Range = \int_0^E \left( -\frac{dE}{dx} \right)^{-1} dE$$



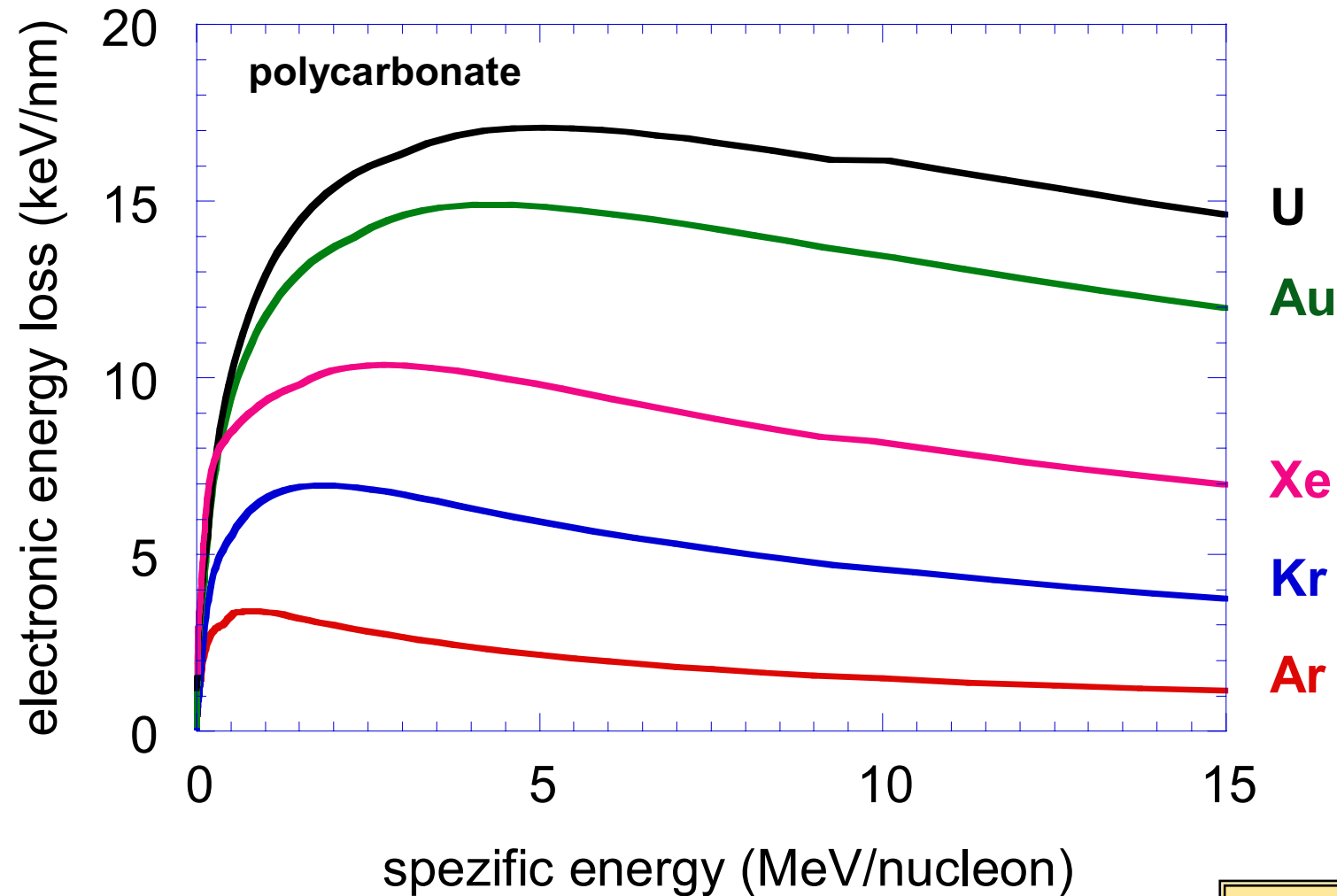
e.g. 11 MeV/u:  $^{40}\text{Ar} \rightarrow 11 \times 40 = 440 \text{ MeV}$   
 $^{238}\text{U} \rightarrow 11 \times 238 = 2.6 \text{ GeV}$

# Energy deposition process



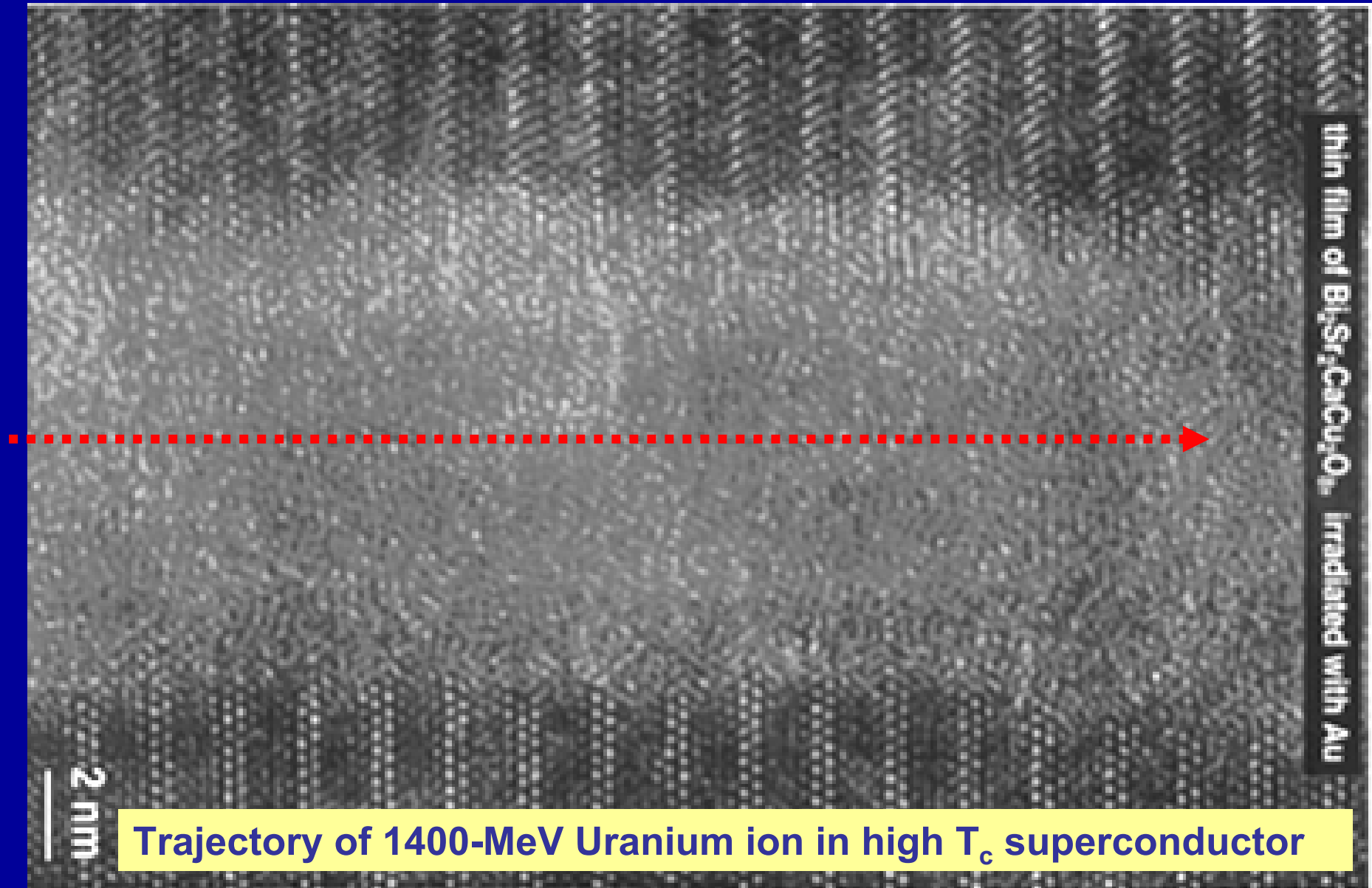
## electronic energy loss – stopping power

$$dE/dx \sim Z_{\text{eff}}^2(\text{ion}) \cdot Z(\text{target})$$



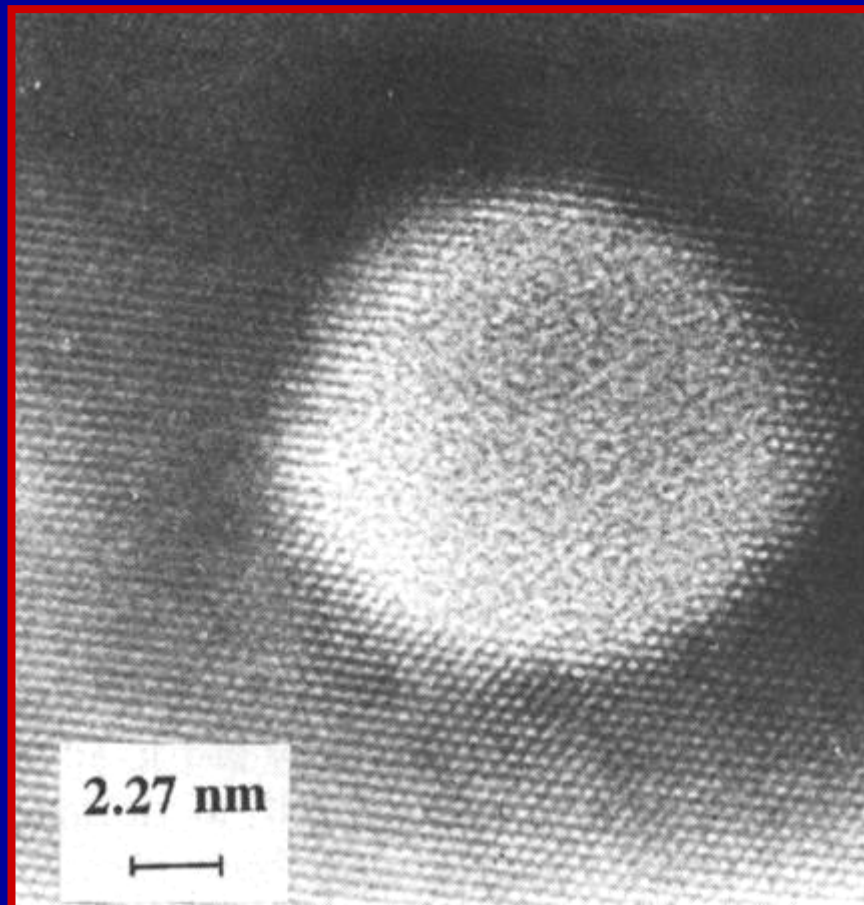
SRIM code

# High resolution transmission electron microscopy





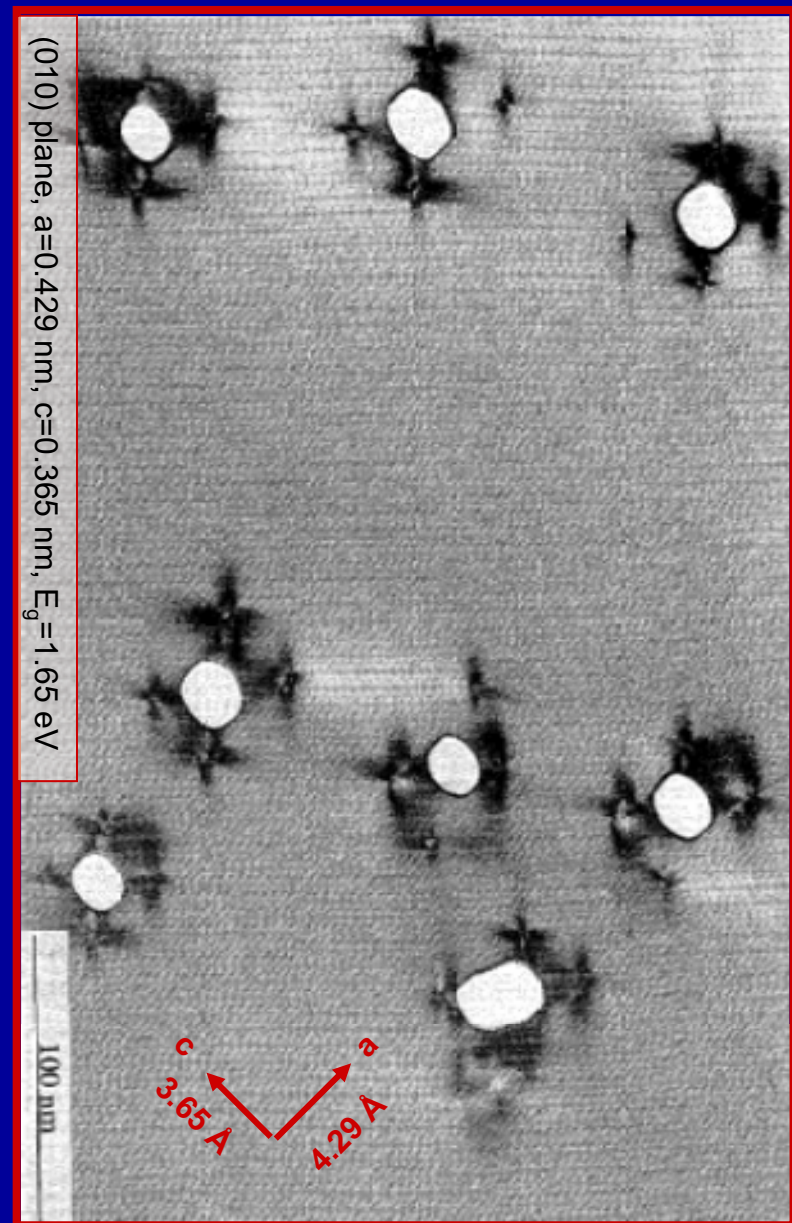
## Tracks in amorphisable material



62 MeV Pb-ions → SiO<sub>2</sub> quartz

Meftah et al., Phys. Rev B 49 (1994) 12457

2.7 GeV U-ions → GeS



Vetter et al., NIMB 91(1994) 129

# Material sensitivity

high sensitivity

low sensitivity

dE/dx  
threshold

~1 keV/u

~20 keV/u

~50 keV/u

## insulators

😊 oxides, spinels

😊 ionic crystals

😊 polymers

## semi-conductors

😊 amorphous Si

😊 GeS, InP, Si<sub>1-x</sub>Ge<sub>x</sub>

😞 Si, Ge

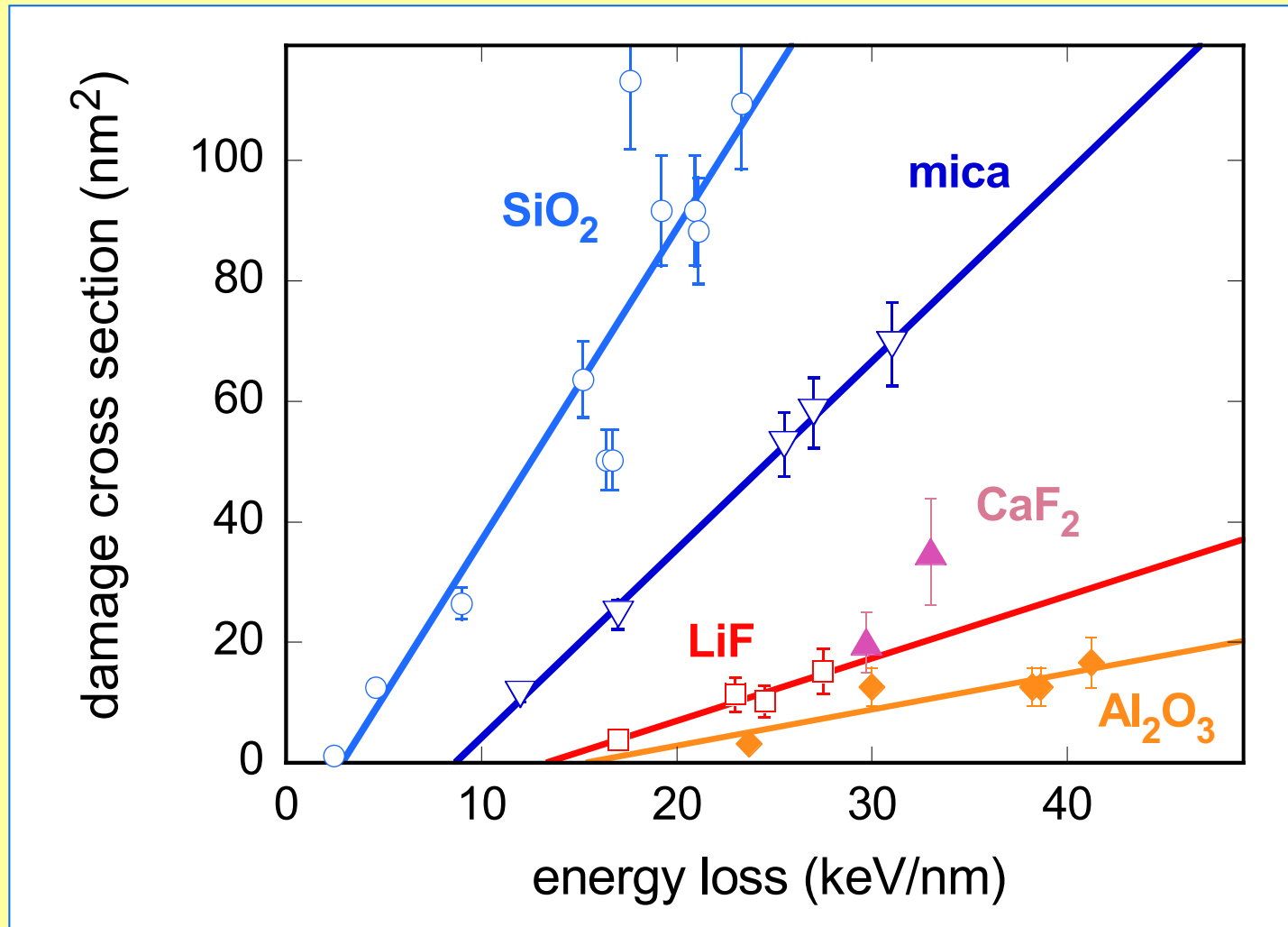
## metals

😊 amorphous alloys

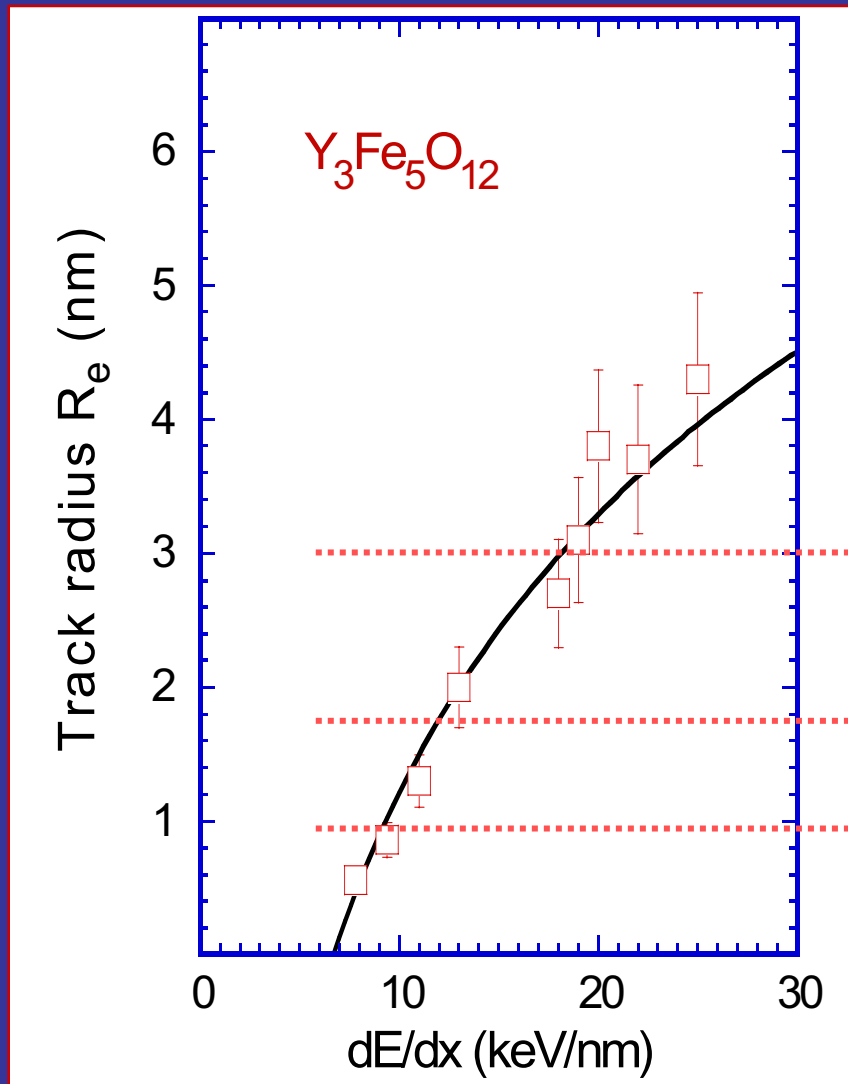
😞 Fe, Bi, Ti, Co, Zr

😞 Au, Cu, Ag...

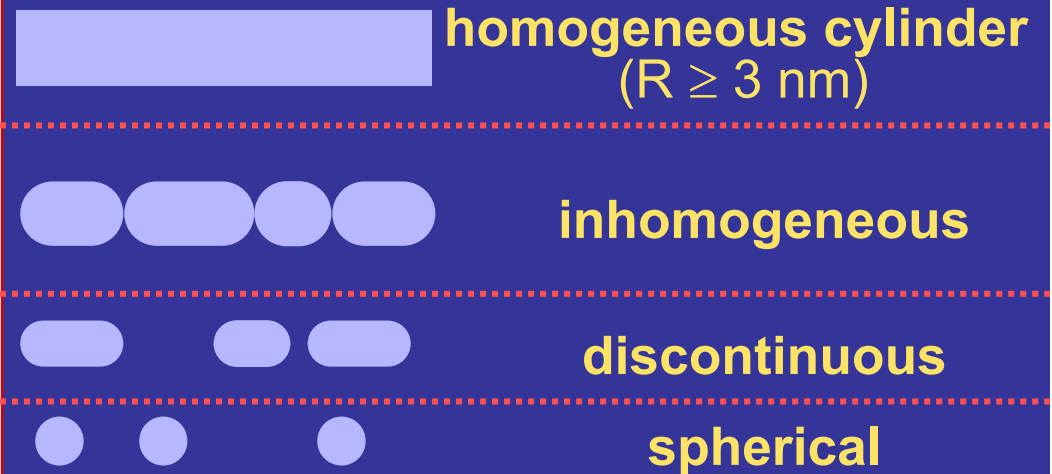
# Track formation threshold



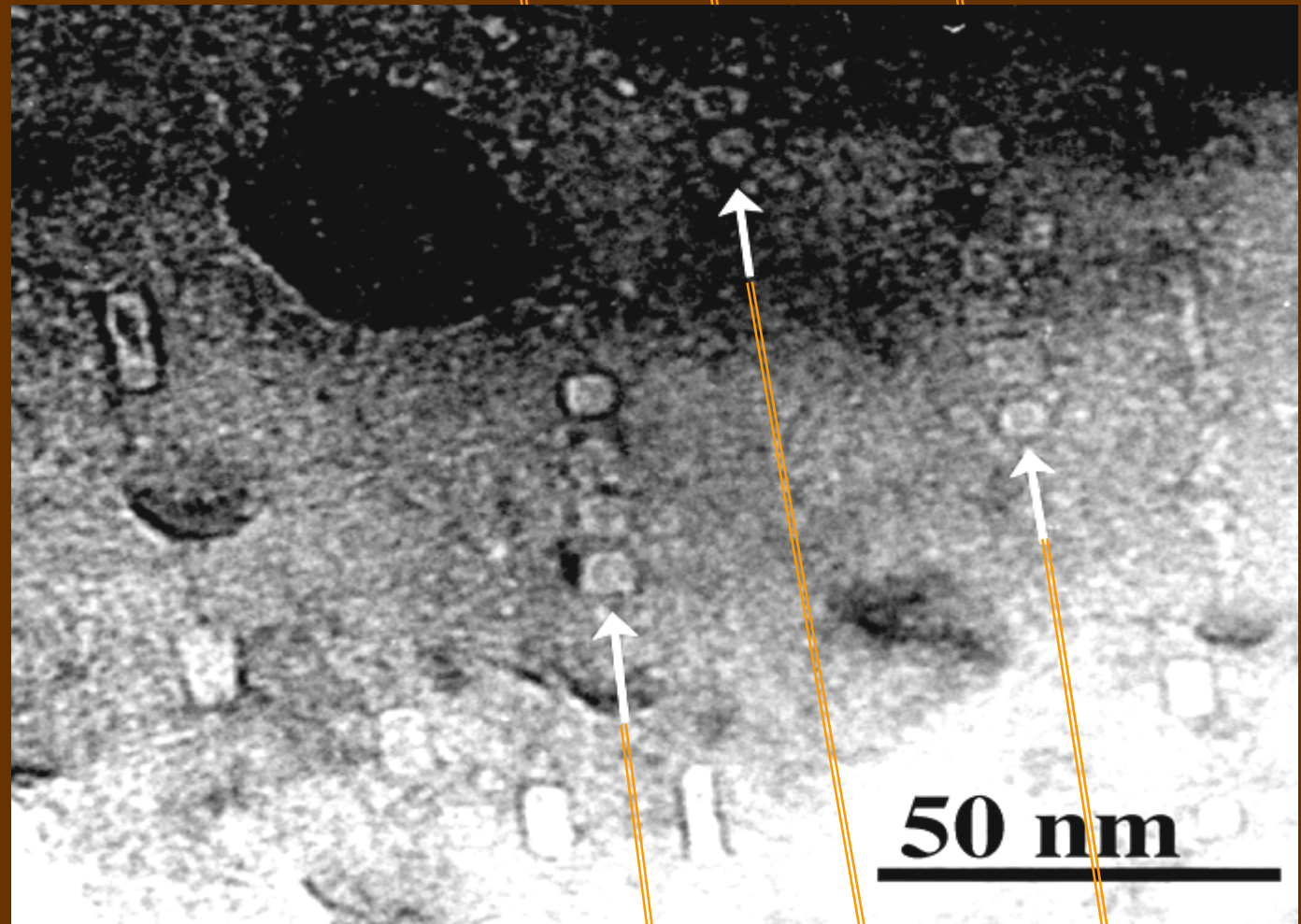
# Track size versus energy loss



## damage morphology

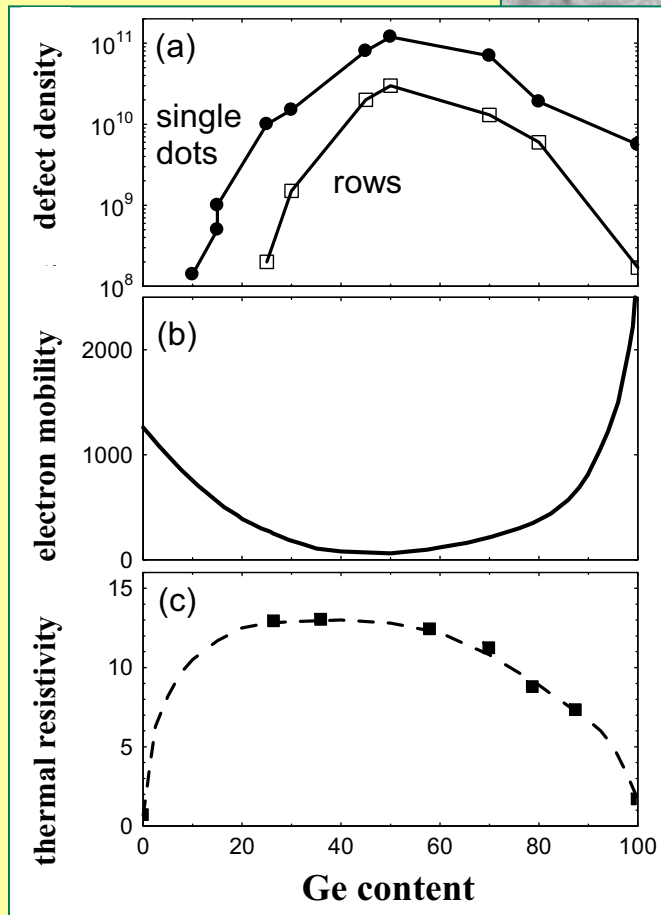


**11.1 MeV/u Bi  $\rightarrow$  CaF<sub>2</sub>**

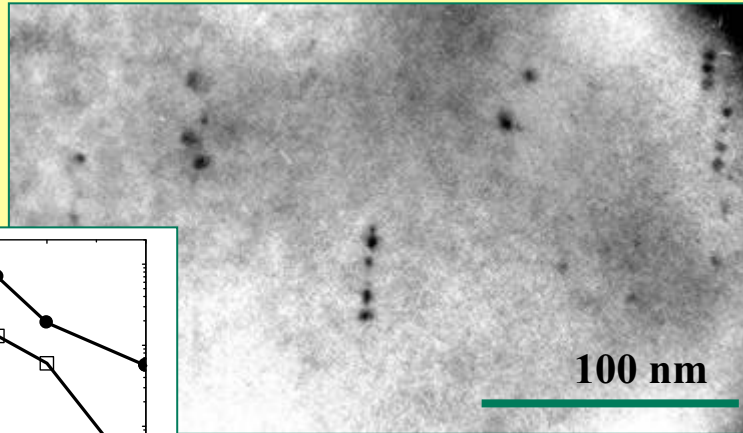


Khalifaoui et al, NIMB 240 (2005) 819

# discontinuous tracks in semiconducting compounds



Gaiduk et al, PRB 66 (2002) 045316  
Physica B 340 (2003) 808



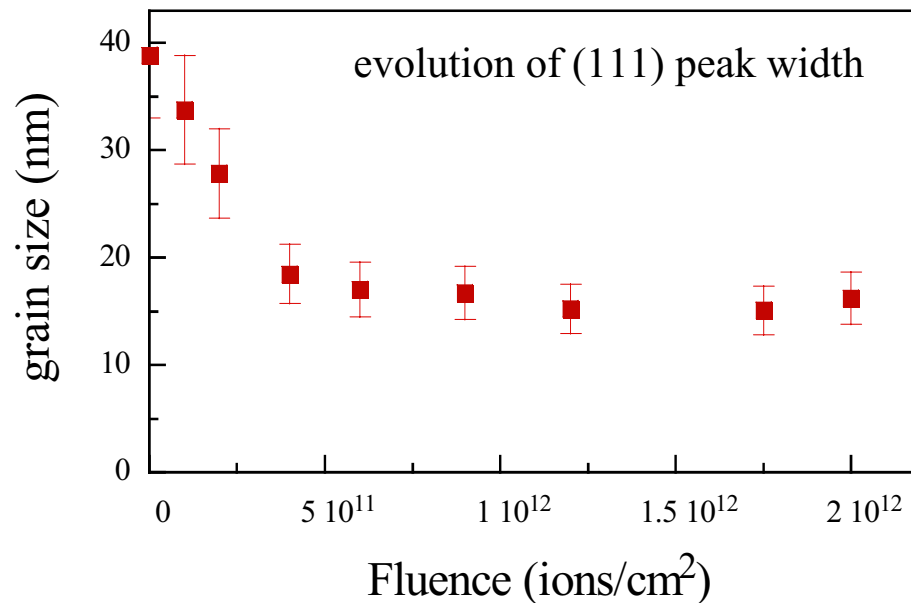
L. Chadderton



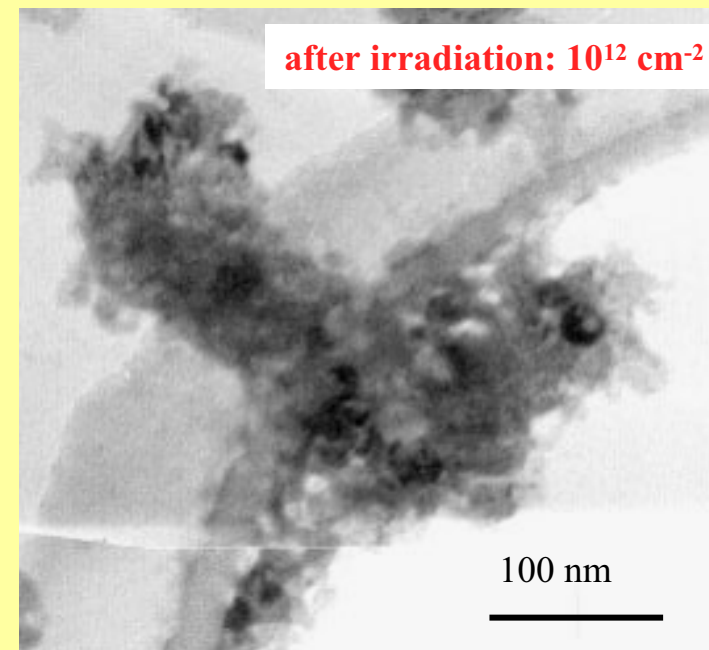
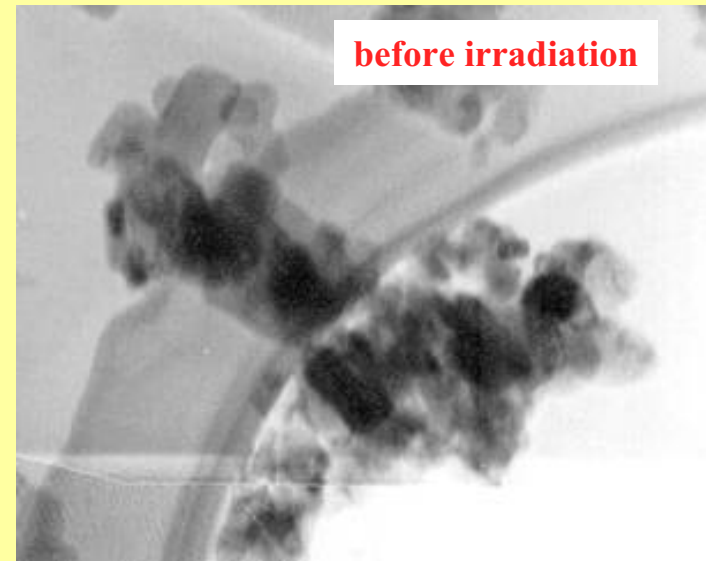
# Beam-induced grain breaking

4 MeV/u Pb  $\rightarrow$  CaF<sub>2</sub> powder

in-situ X-ray diffraction



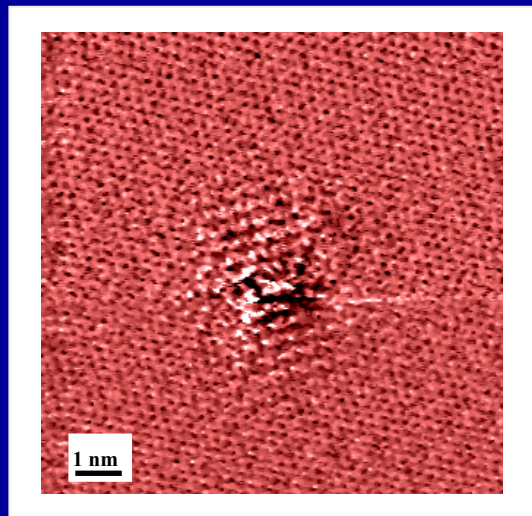
40 nm  $\rightarrow$  20 nm grains



Boccanfuso, PhD thesis, Caen, (2001)  
Boccanfuso et al. NIMB 175-177 (2001) 590  
NIMB 191 (2002) 301

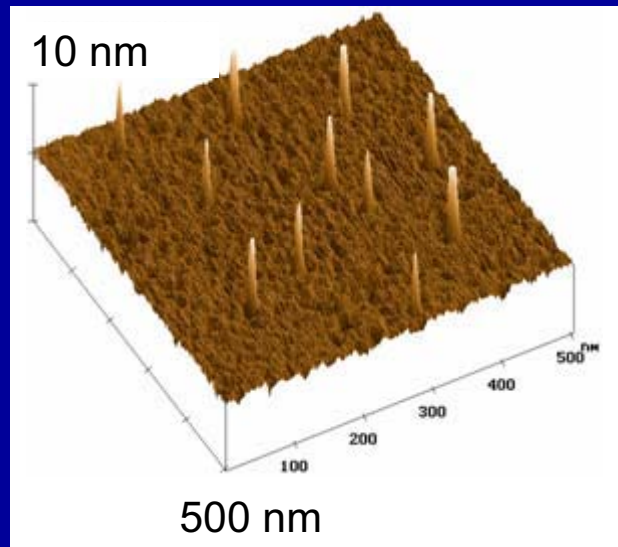
# Tracks at sample surface

graphite (HOPG)



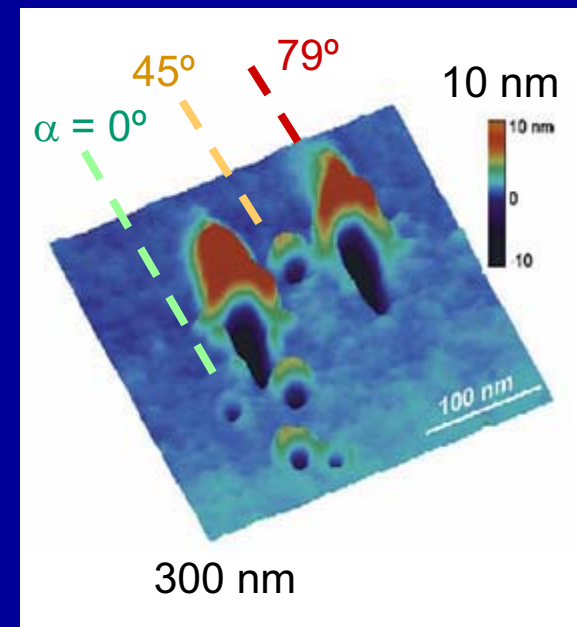
Liu, PRB 64 (2001)

ionic crystal  $\text{CaF}_2$



Khalfaoui NIMB 240 (2005)

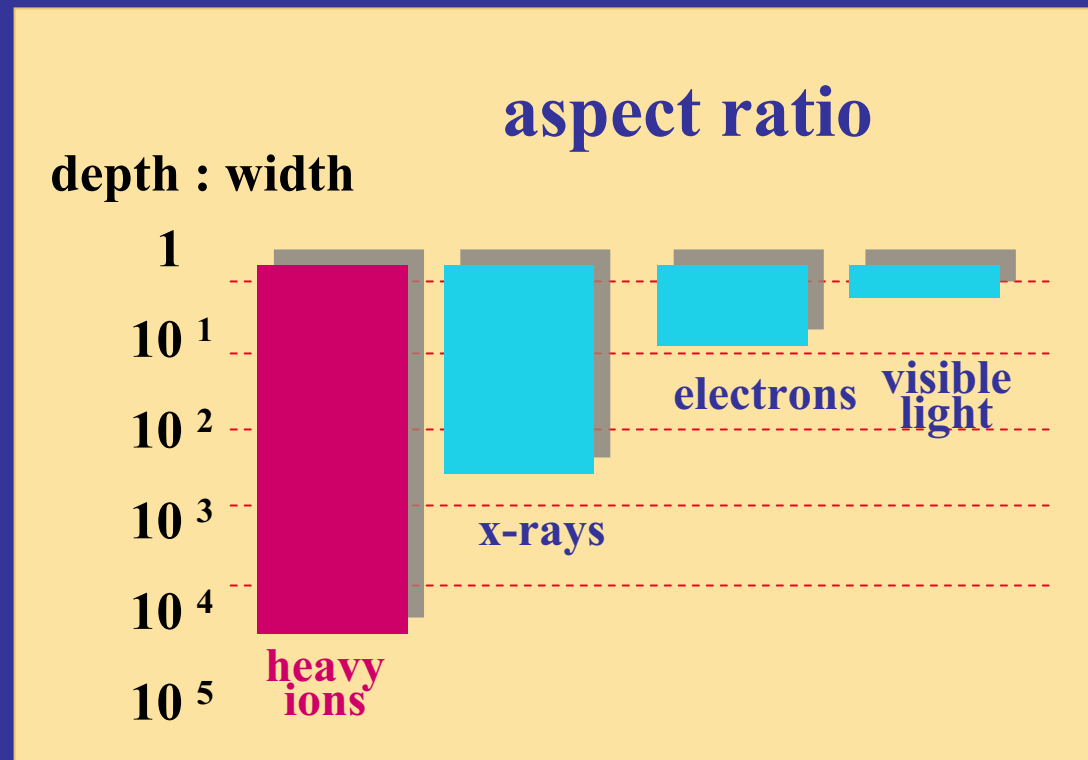
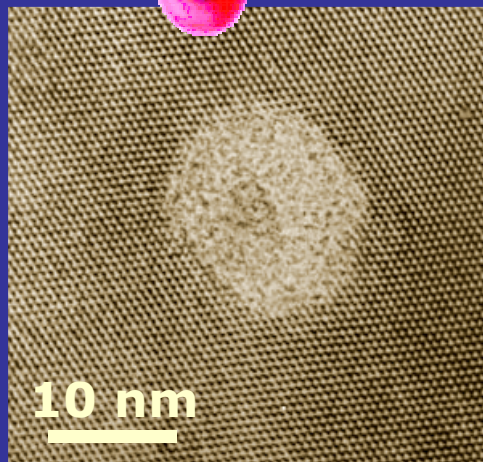
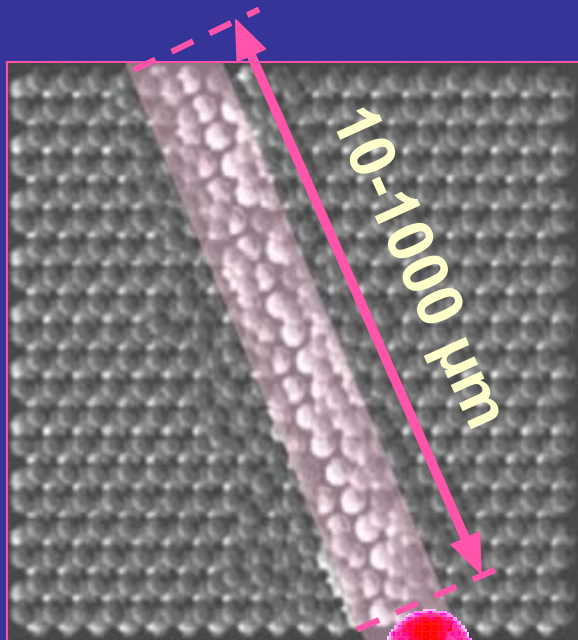
polymer (PMMA)



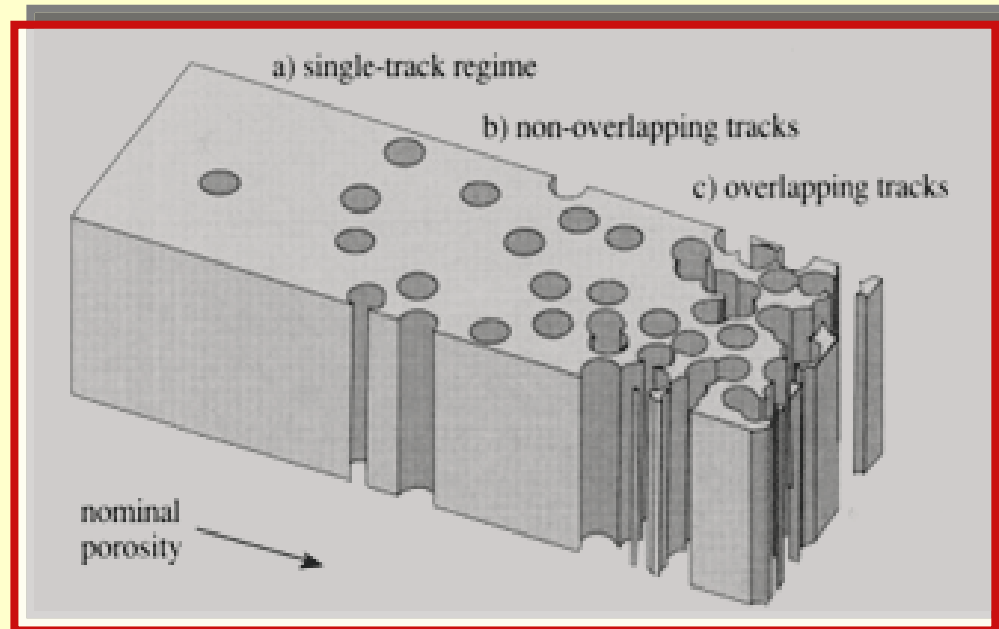
Papaléo, NIMB 206 (2001)



# MeV-GeV ions as structuring tool



# Irradiation Parameters

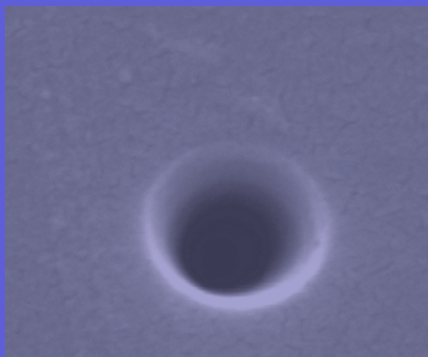


ion species ..C...Xe...U

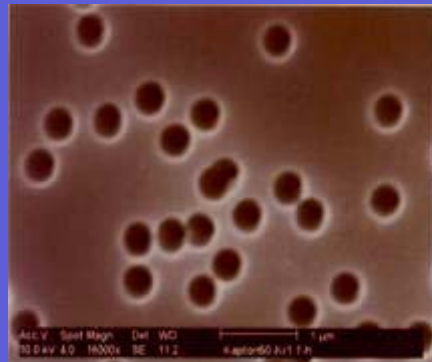
energy: 1 – 10 MeV/u

fluence: 1 ...  $10^{13}$  ions/cm<sup>2</sup>

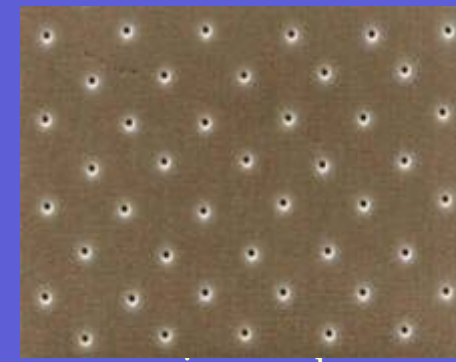
single ion



random



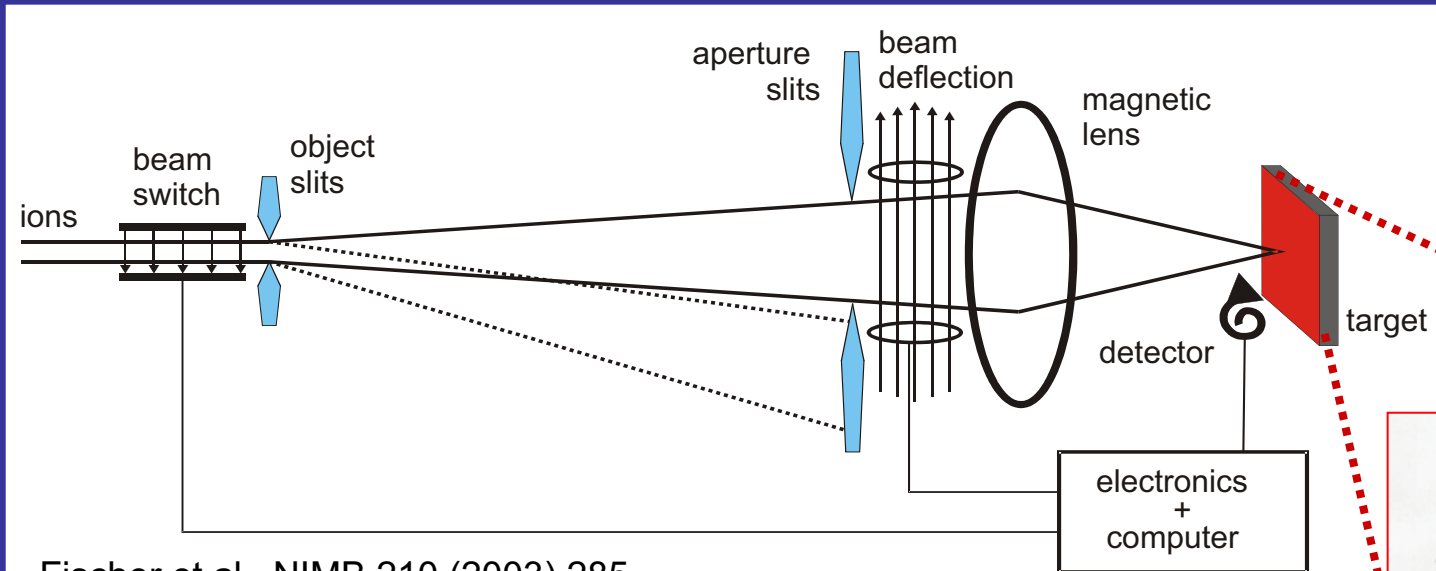
ordered



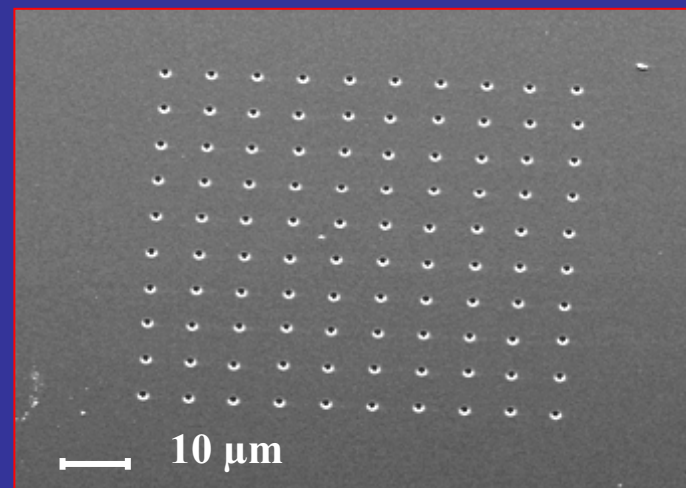
micro probe

# Heavy-ion microprobe

## Positioning of single ions

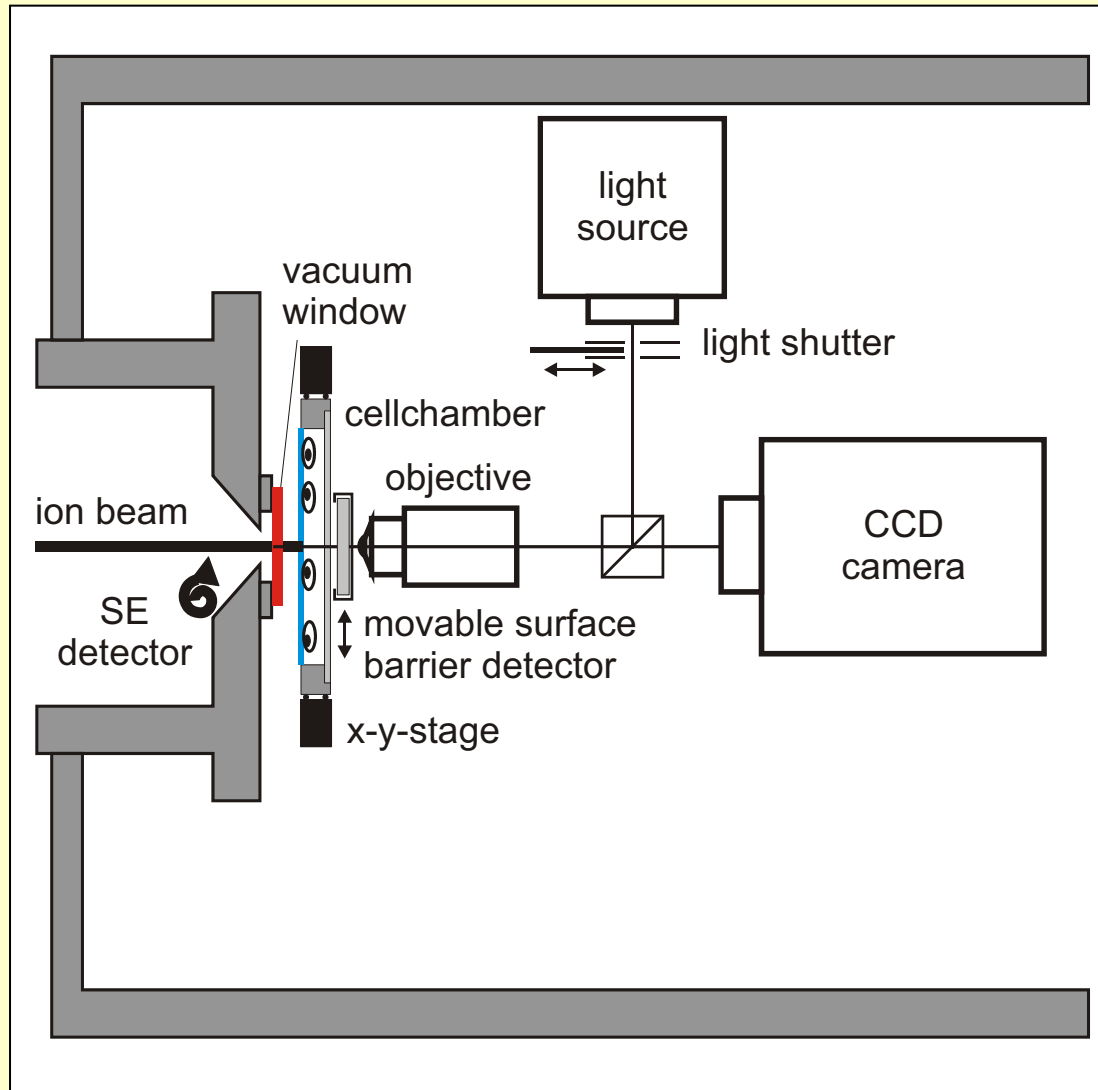


Fischer et al., NIMB 210 (2003) 285



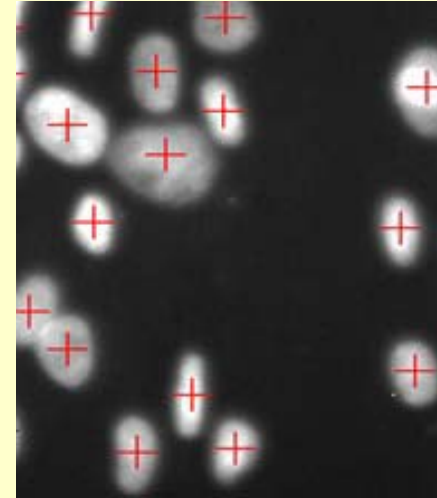
Fischer et al. NIMB 158 (1999) 245

# Irradiation setup for cell irradiation

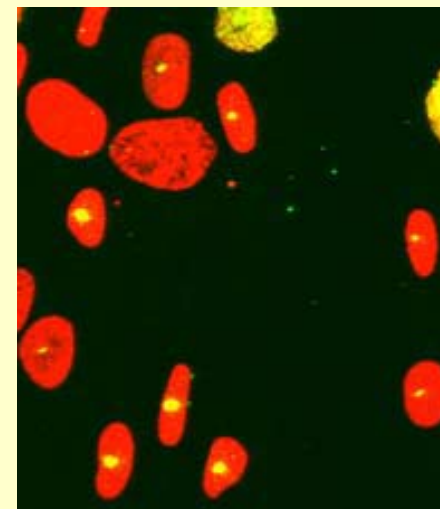


Heiss, PhD Thesis, Darmstadt (2004)  
Radiation Research 165 (2006) 231

- **stained cell nuclei automatically indexed by microscope and CCD camera**

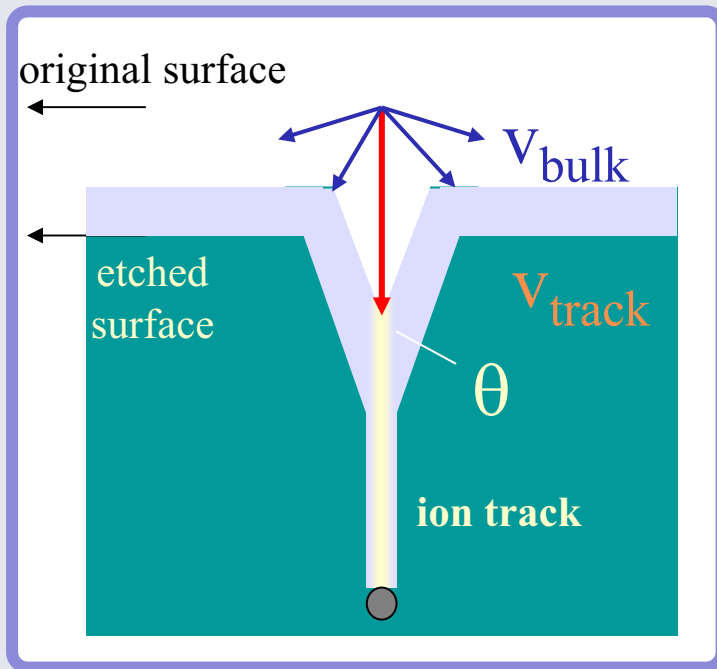


- **ion irradiation with microprobe**
- **ion hits made visible by immuno staining**

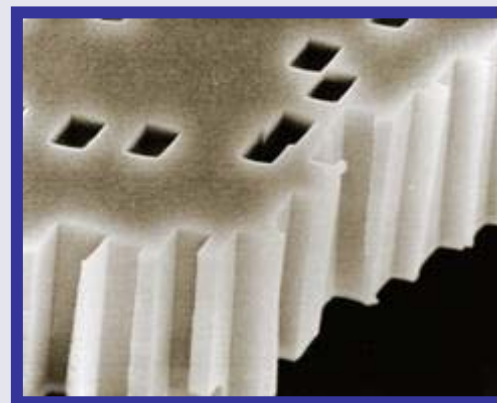
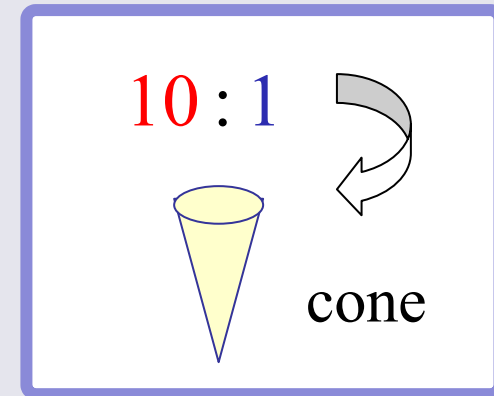
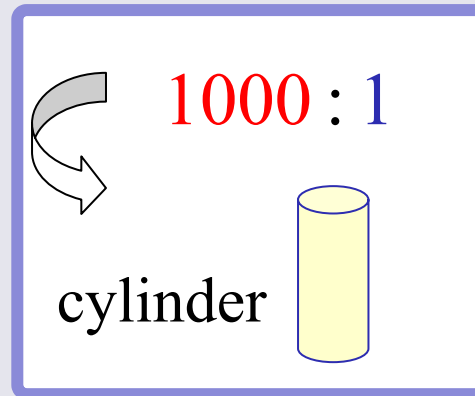


# Control of pore geometry

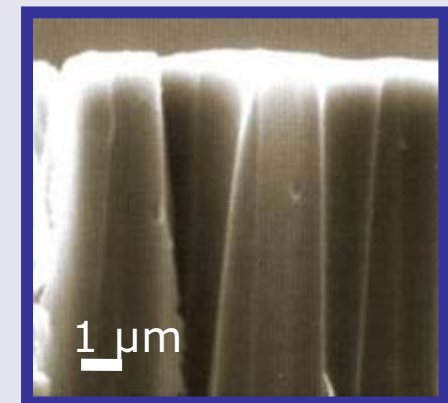
$$V_{\text{track}} : V_{\text{bulk}} = \sin \theta \rightarrow \text{pore geometry}$$



chemical etchant  
(e.g., NaOH, NaOCl, H<sub>2</sub>SO<sub>4</sub>)

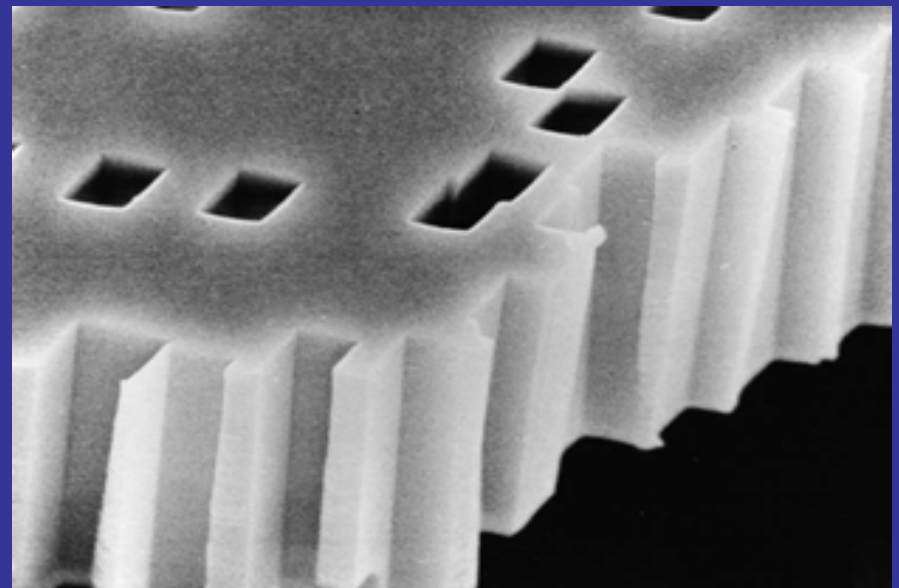
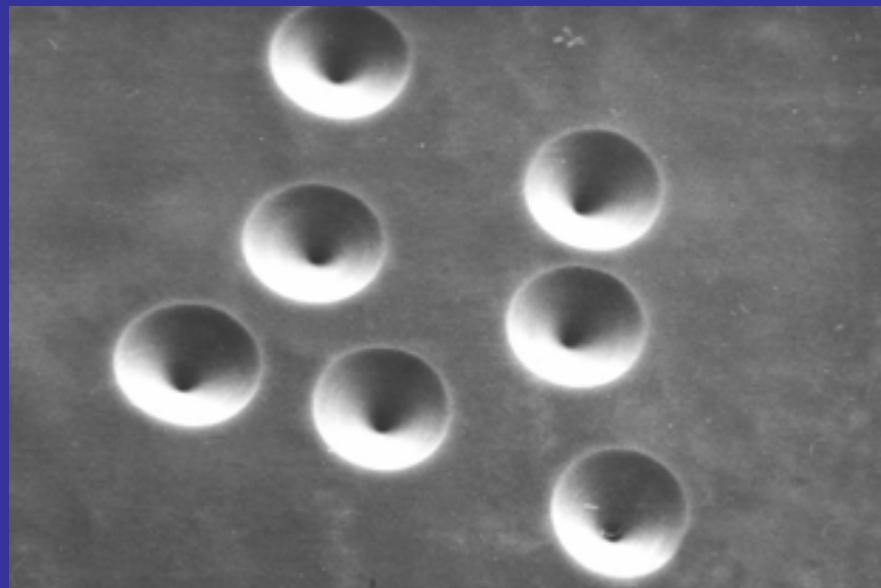
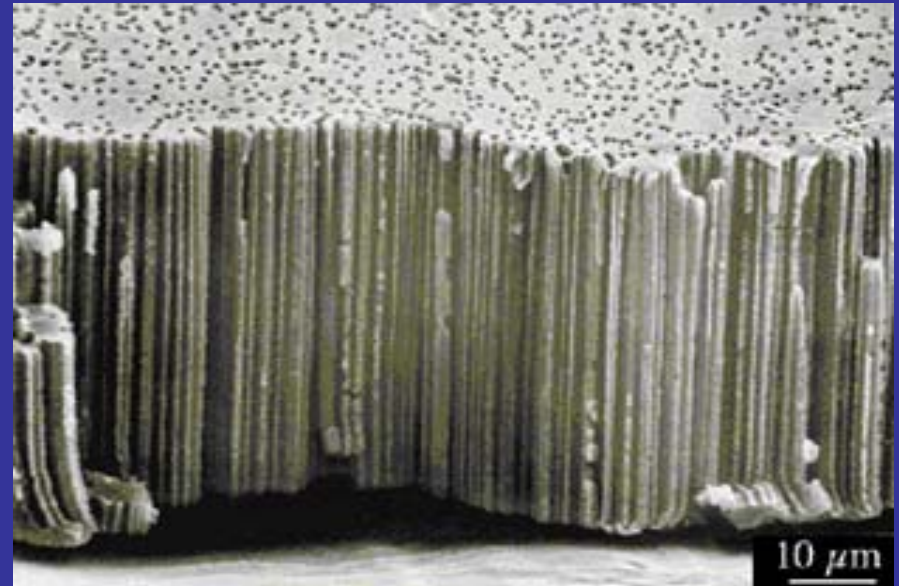
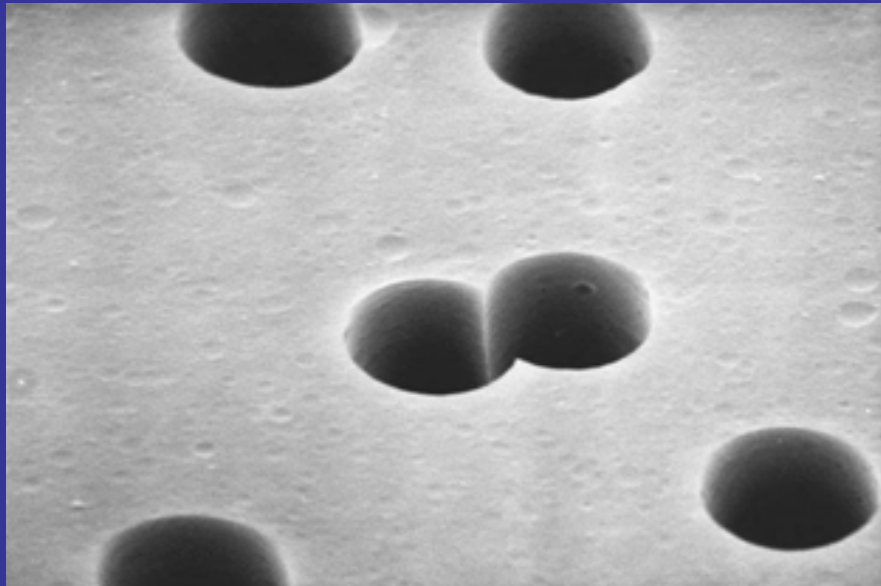


mica

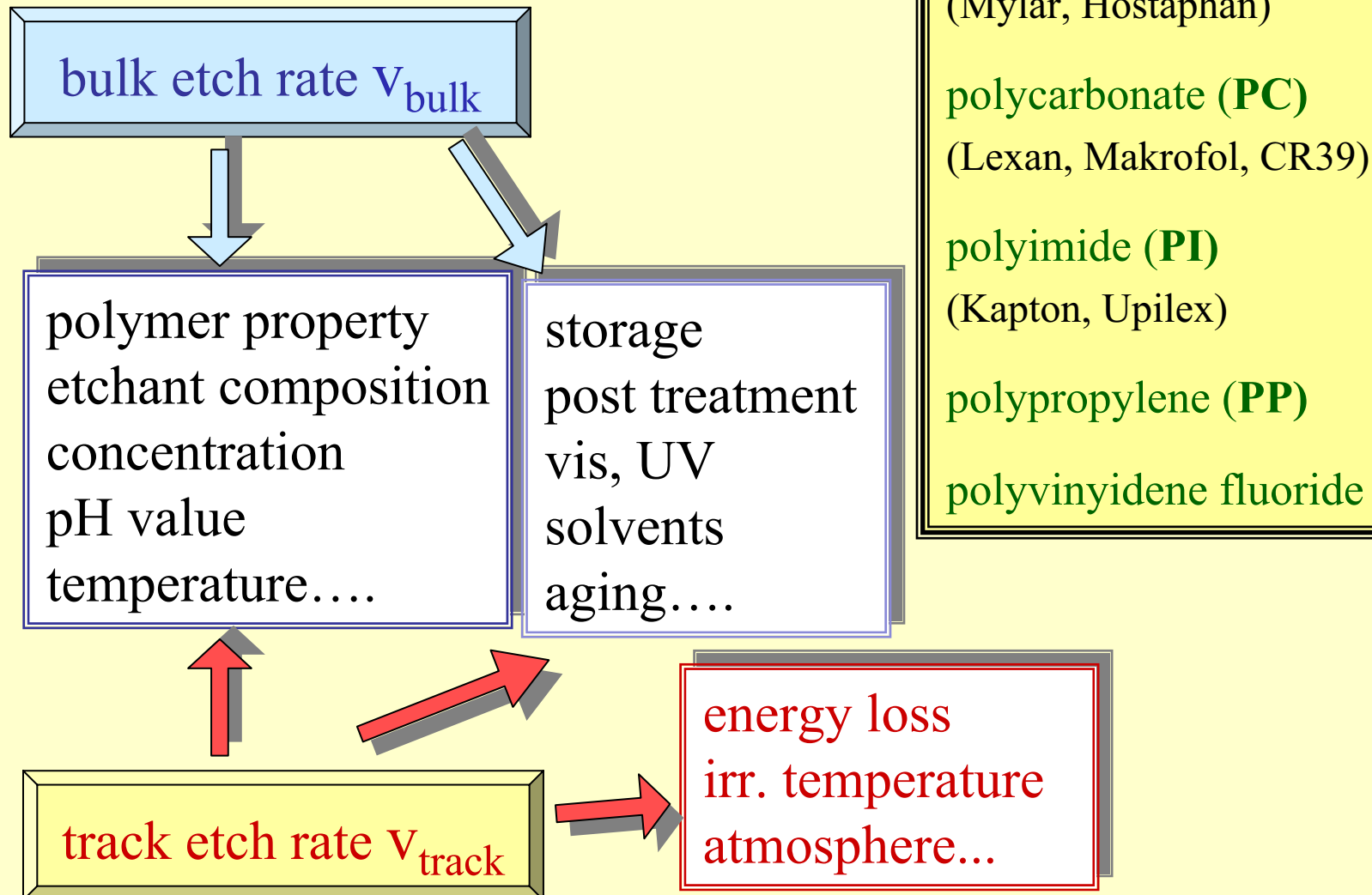


Kapton





# Track etching process



## POLYMERS

polyethylene terephthalate (**PET**)  
(Mylar, Hostaphan)

polycarbonate (**PC**)  
(Lexan, Makrofol, CR39)

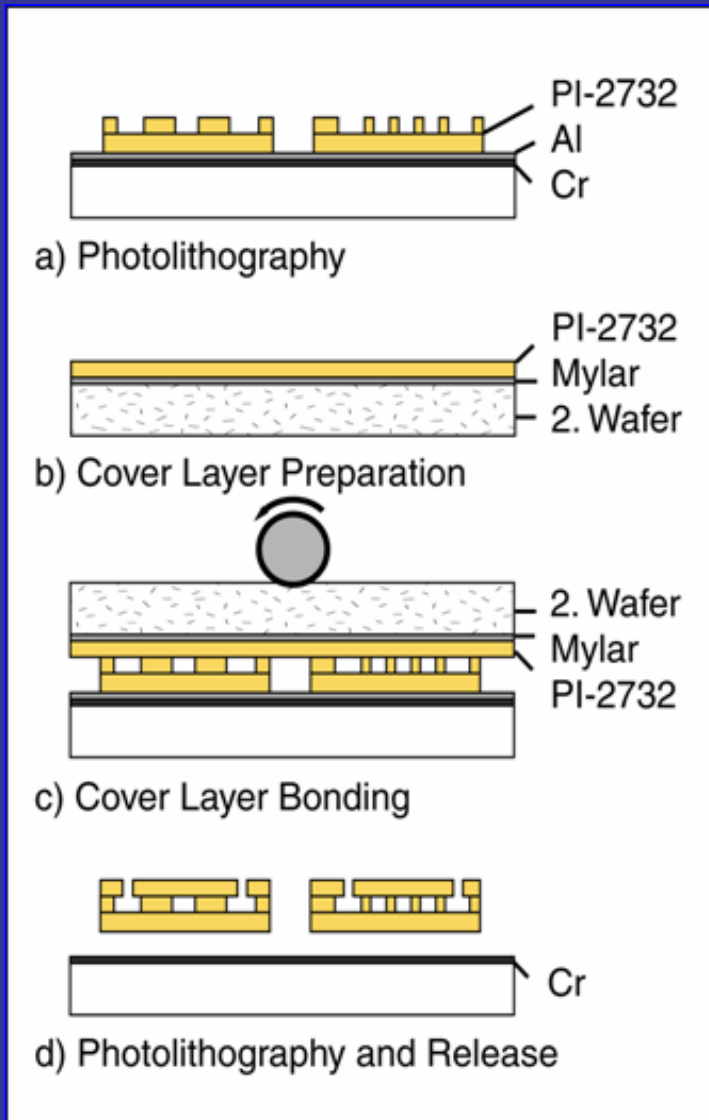
polyimide (**PI**)  
(Kapton, Upilex)

polypropylene (**PP**)

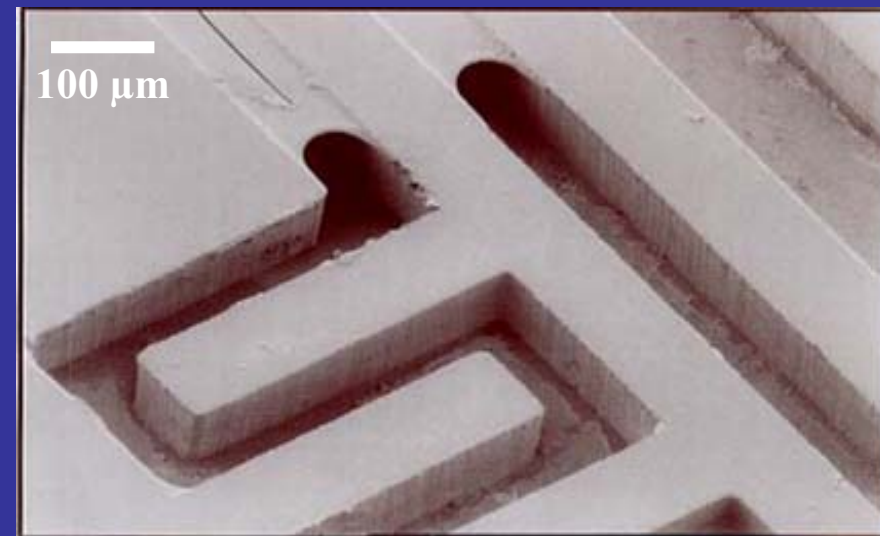
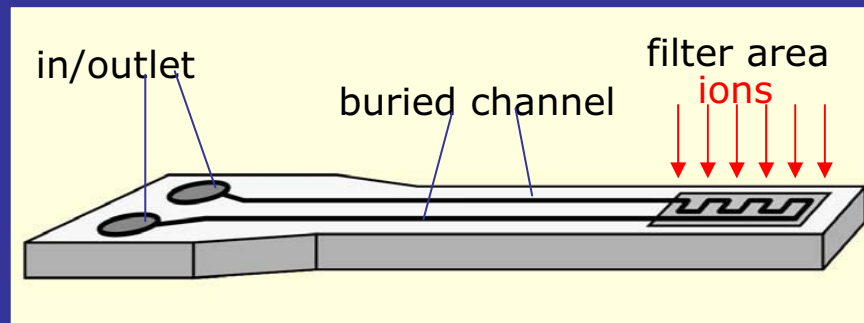
polyvinylidene fluoride (**PVDF**)



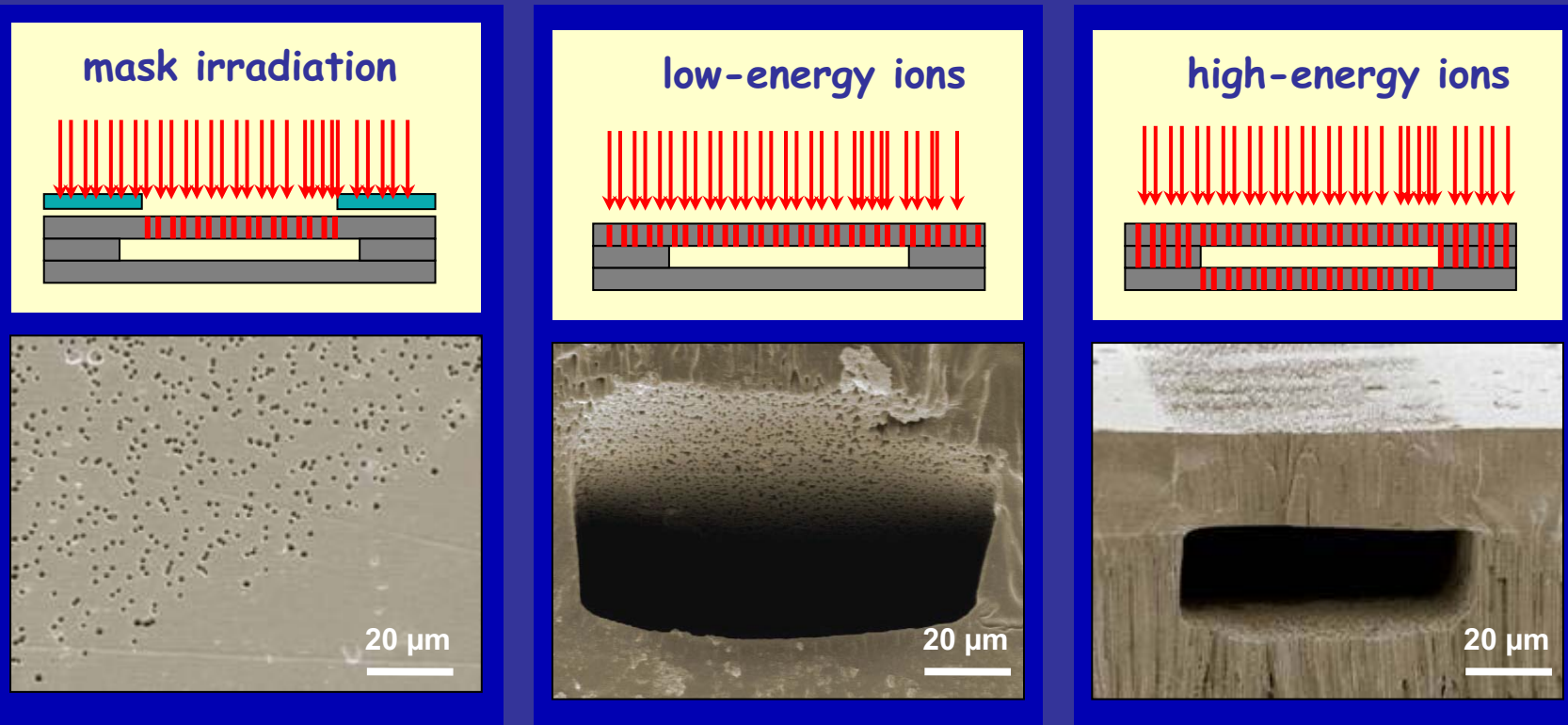
# **Ion track technology & microfluidic systems**



**fabricated by photolithography,  
bonding, and annealing**



# Integration of microporous membrane



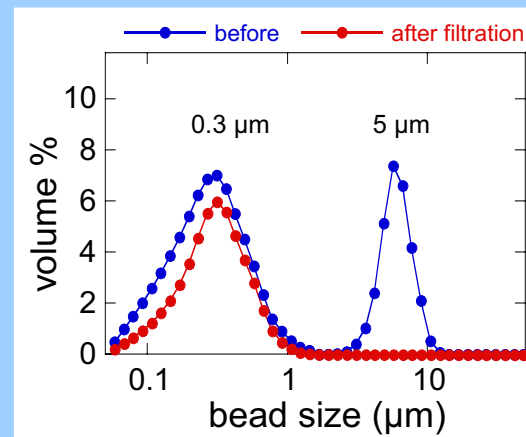
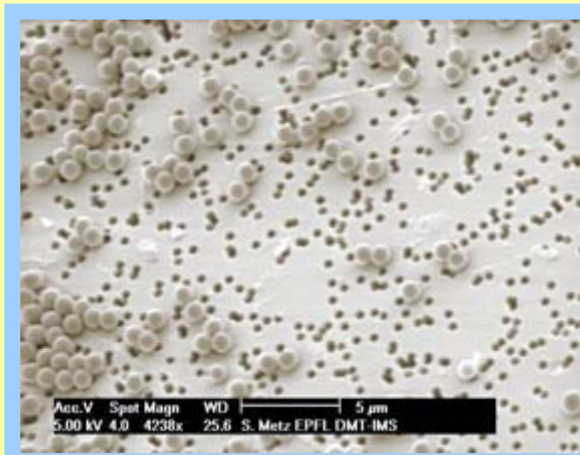
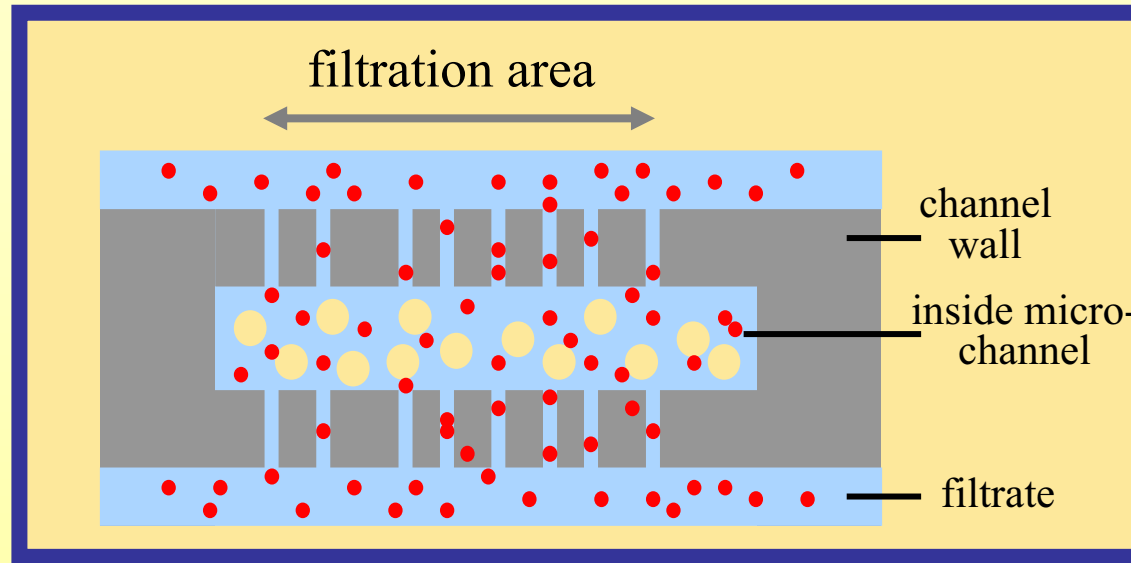
**control  
parameters**

mask  
ion energy  
ion fluence  
etch time

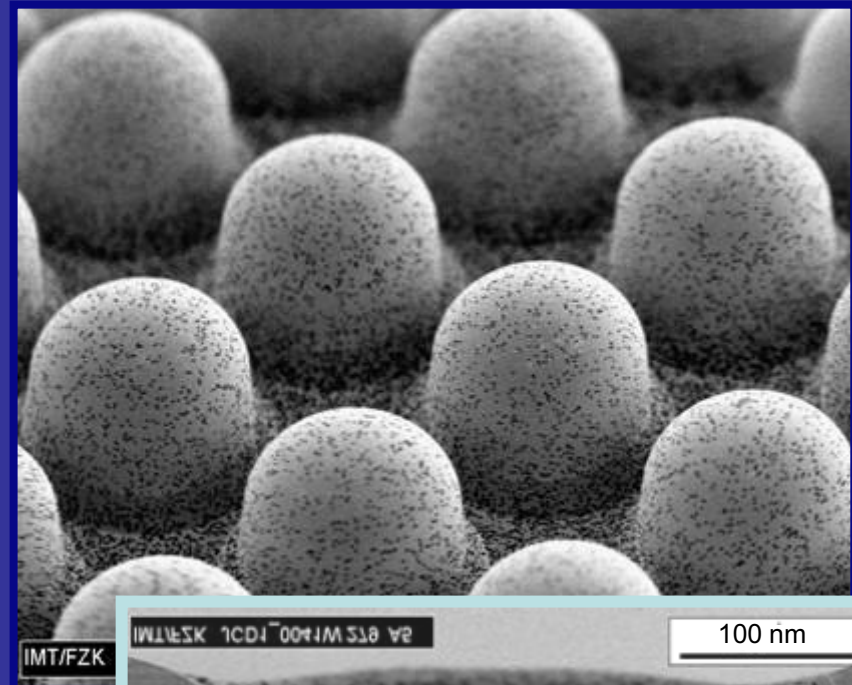
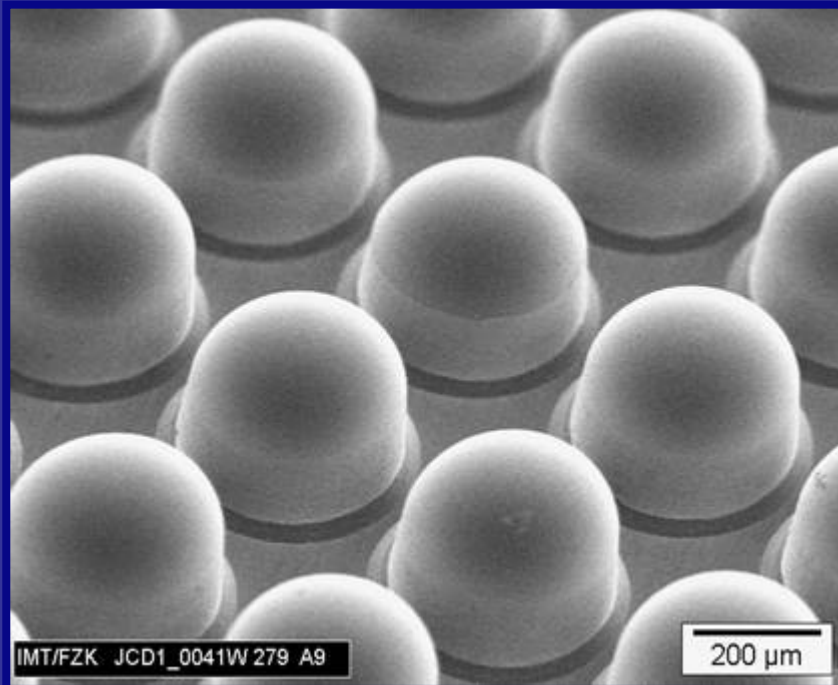


filter area  
structural depth  
pore density  
pore size

# Microfluid filtration with nanopores

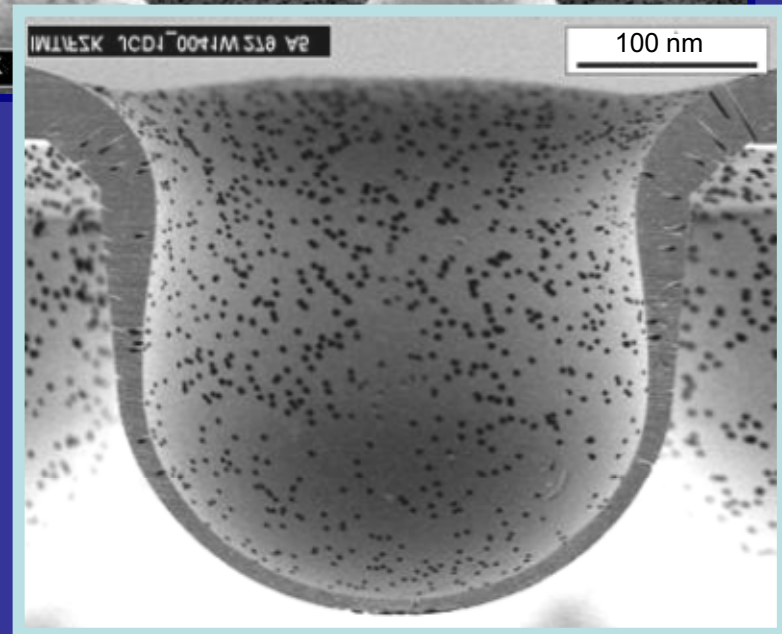


# Perforation of thermoformed microcontainers



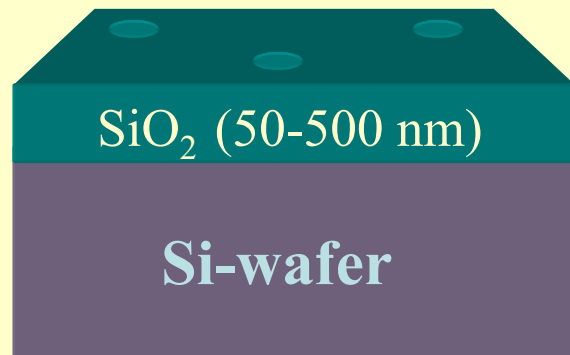
**drainage during growth of cell cultures  
in liquid medium**

Giselbrecht, PhD thesis Karlsruhe 2006  
IEE Proc. Nanobiotechnology 151 (2004) 151



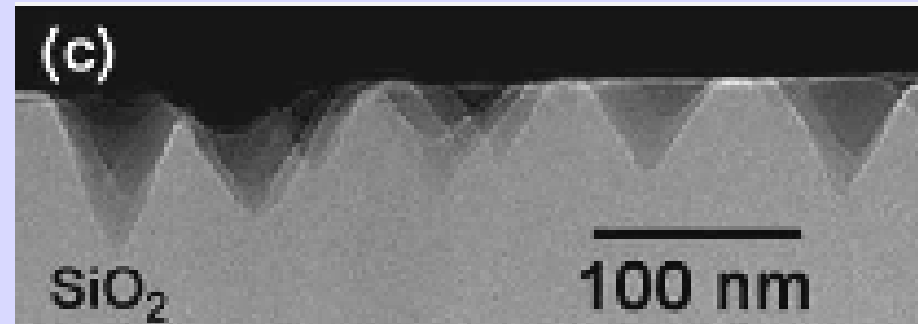
# Compatibility of silicon and ion-beam technology

$\text{SiO}_2$  / Si



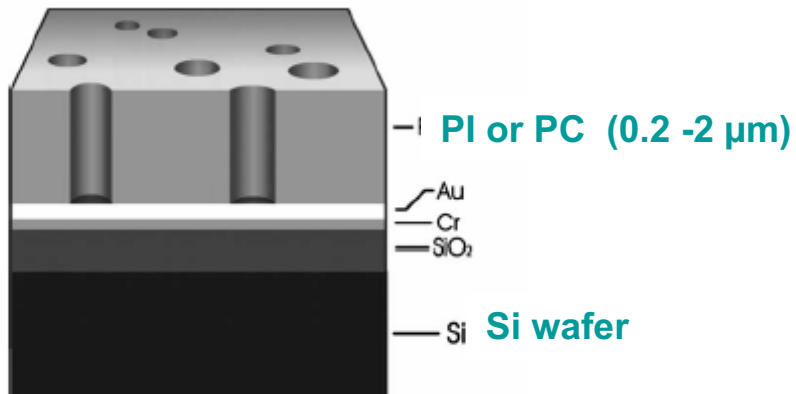
irradiated with 20 MeV Au

cross section of etched ion tracks in  $\text{SiO}_2$  film



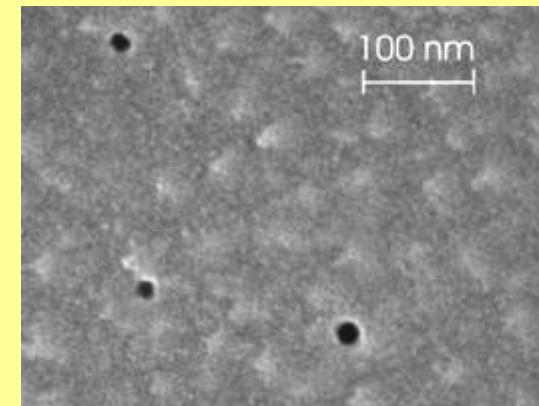
Milanez Silva et al. NIM B 206 (2003) 486

Xe ions (1075 MeV)  $\rightarrow$  polymer resist / Si



Dauginet-De Pra et al. NIMB 196 (2002) 81

etched ion tracks in resist (~10 nm)

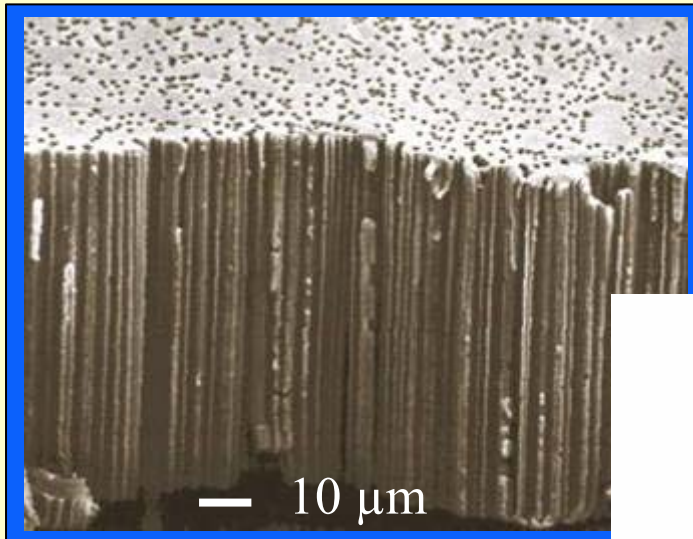


Skupinski et al. NIMB240 (2005) 681

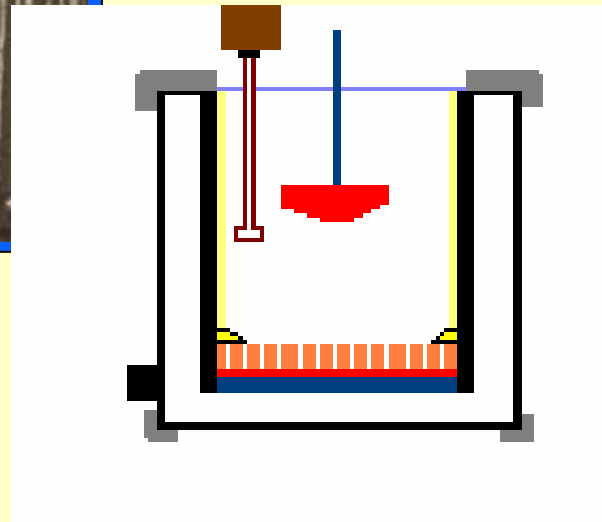


# Ion track membranes as templates

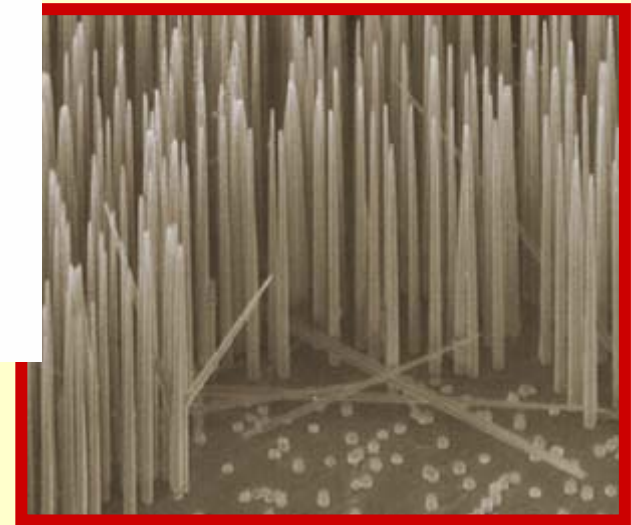
..... from pores to wires .....



etched ion track membrane



filling of pores in galvanic cell



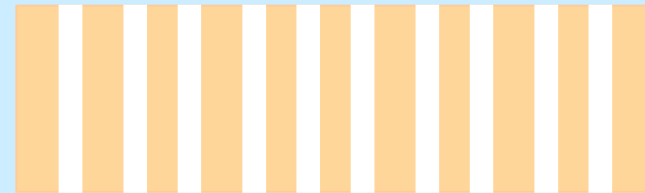
free-standing metal needles



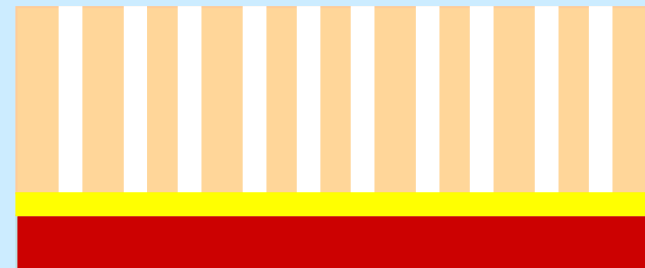
# Template method

Electrochemical deposition in etched ion track membranes

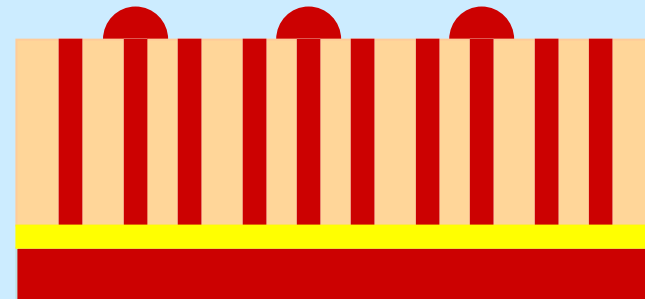
## 1. Membrane



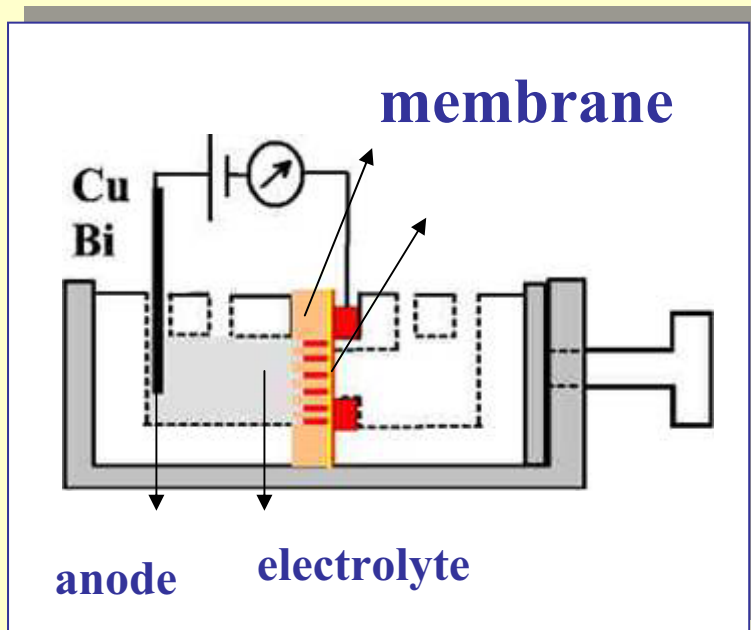
## 2. Au + Cu layer



## 3. Wires and caps



# electrochemical deposition process

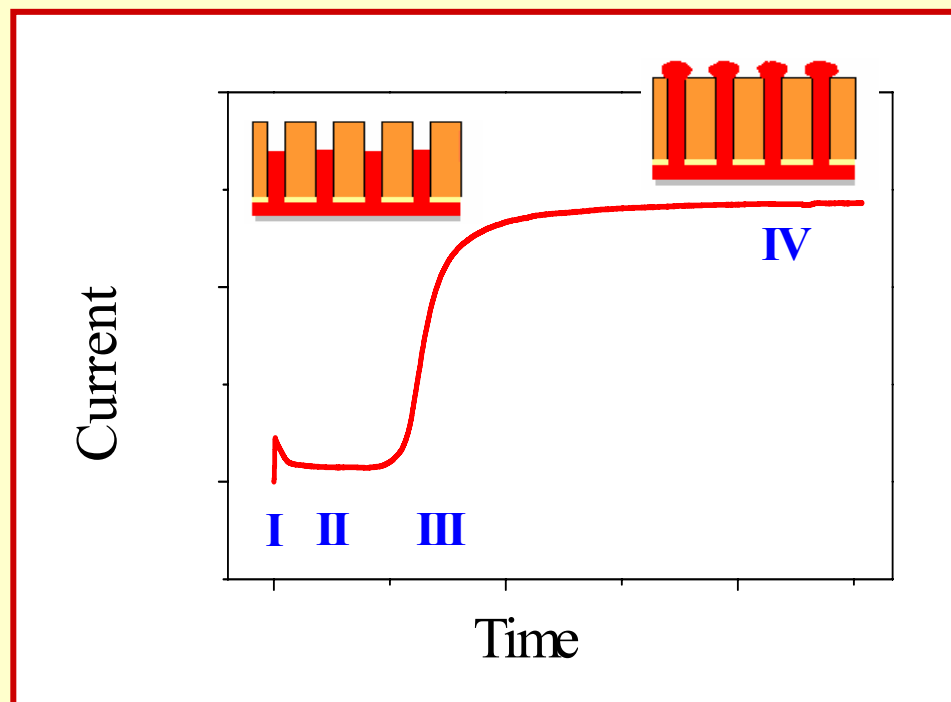
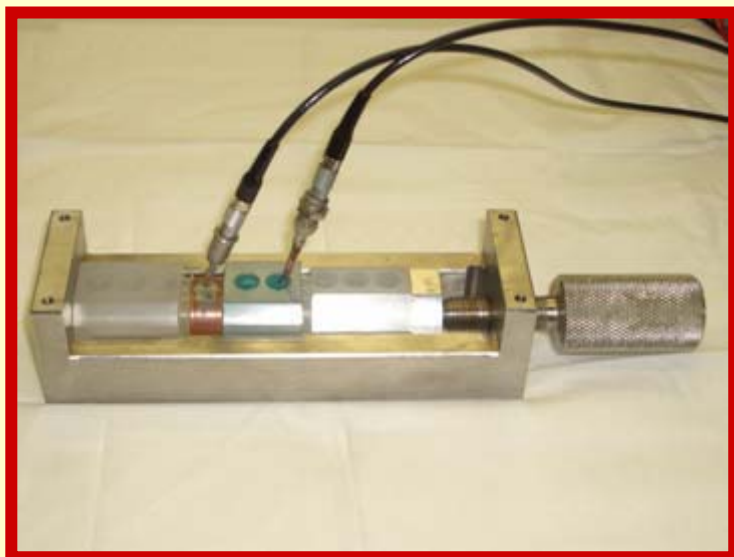


**metals:** Cu, Au, Ni, Fe

**multilayers:** Cu/Co, Cd/Te

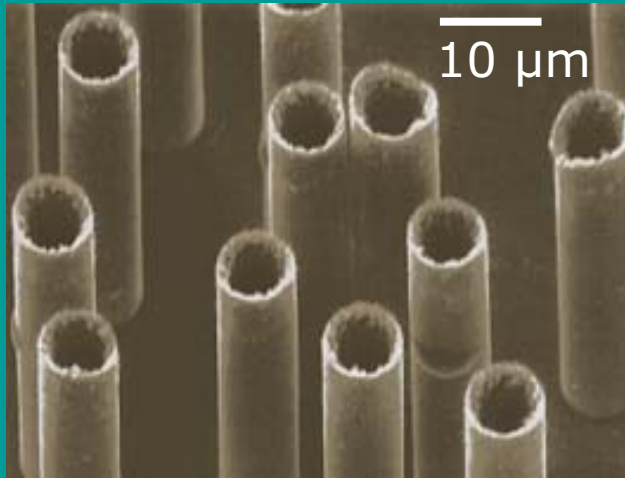
**semimetals:** Bi

**semiconductor:** CdTe, CdS



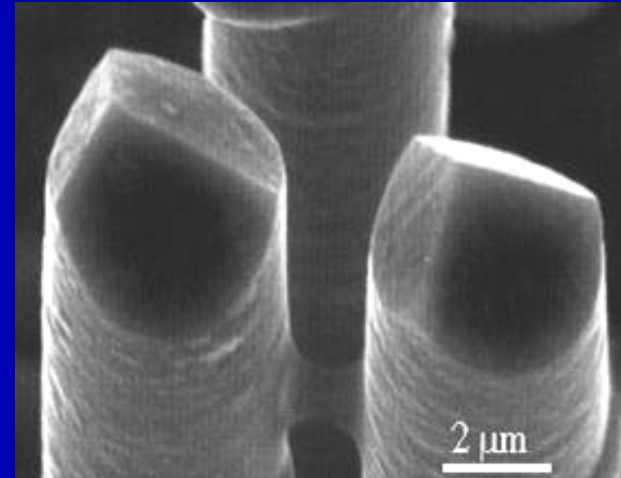
# Microneedles and nanowires

metallic micro-tubes



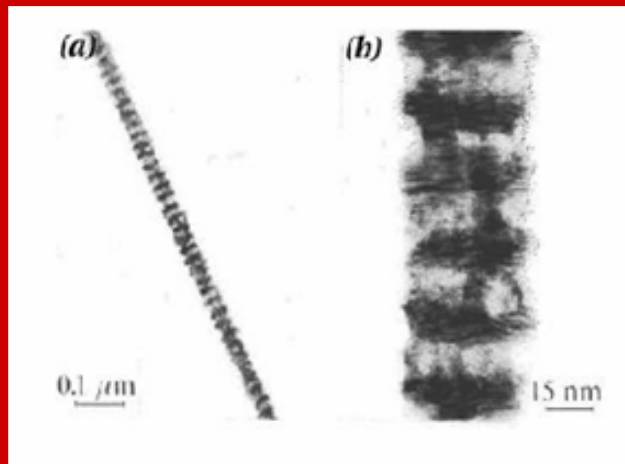
D. Dobrev et al. (GSI)

single-crystalline Cu needles



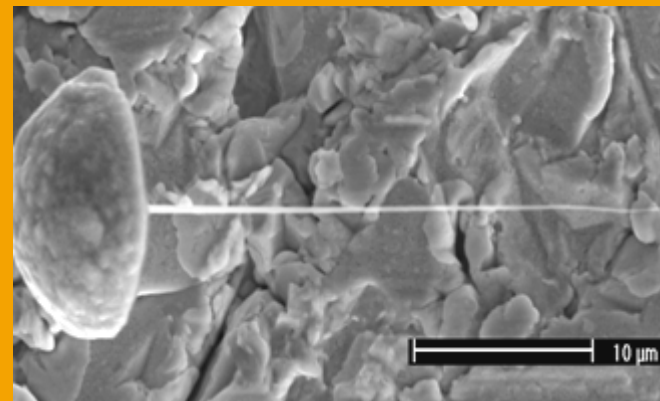
E. Toimil et al. Adv. Mater. 13 (2001) 62

10-nm thick multilayers of Co / Cu



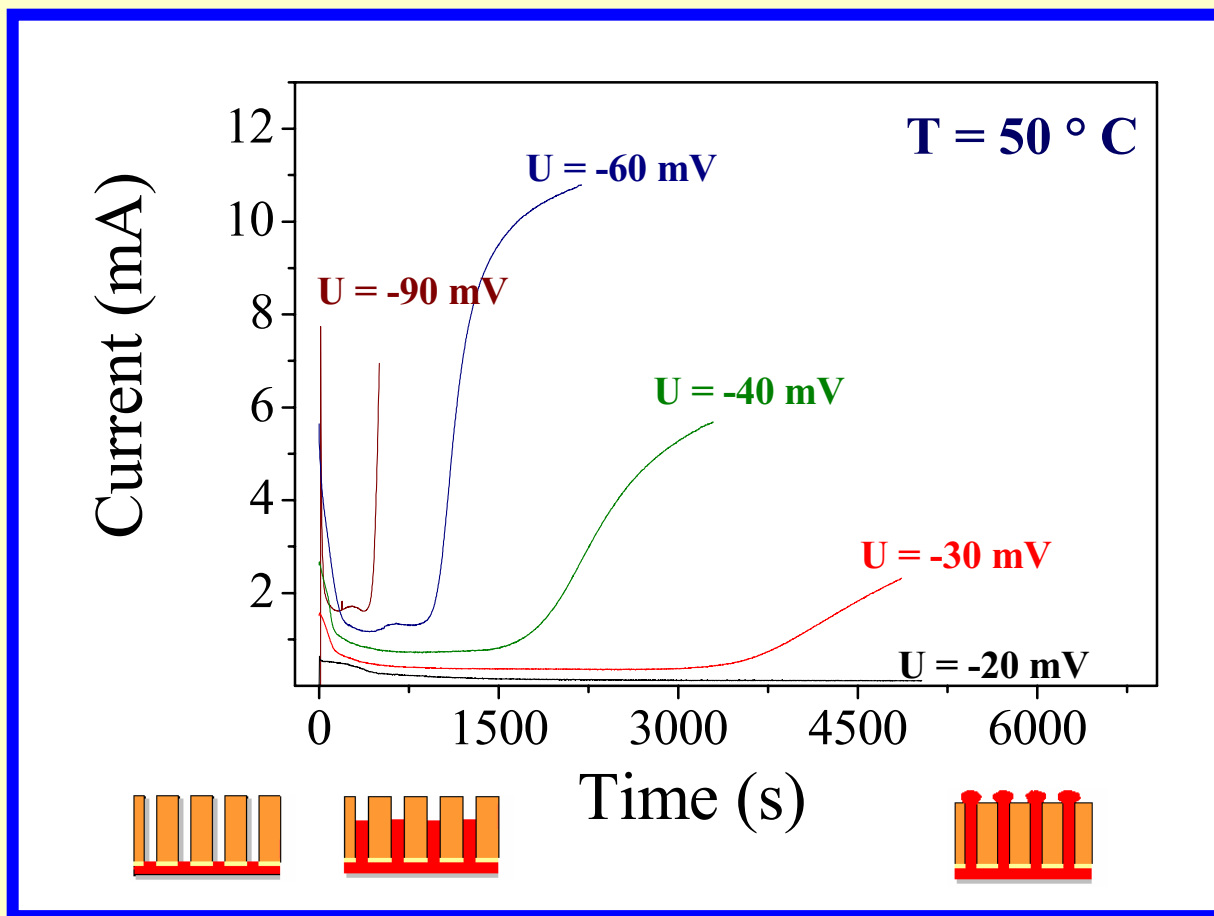
L. Piraux et al., Louvain-la-Neuve

28-nm Co / 14-nm Cu

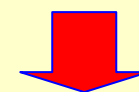


I. Enculescu et. al. (2004)

# Deposition parameters



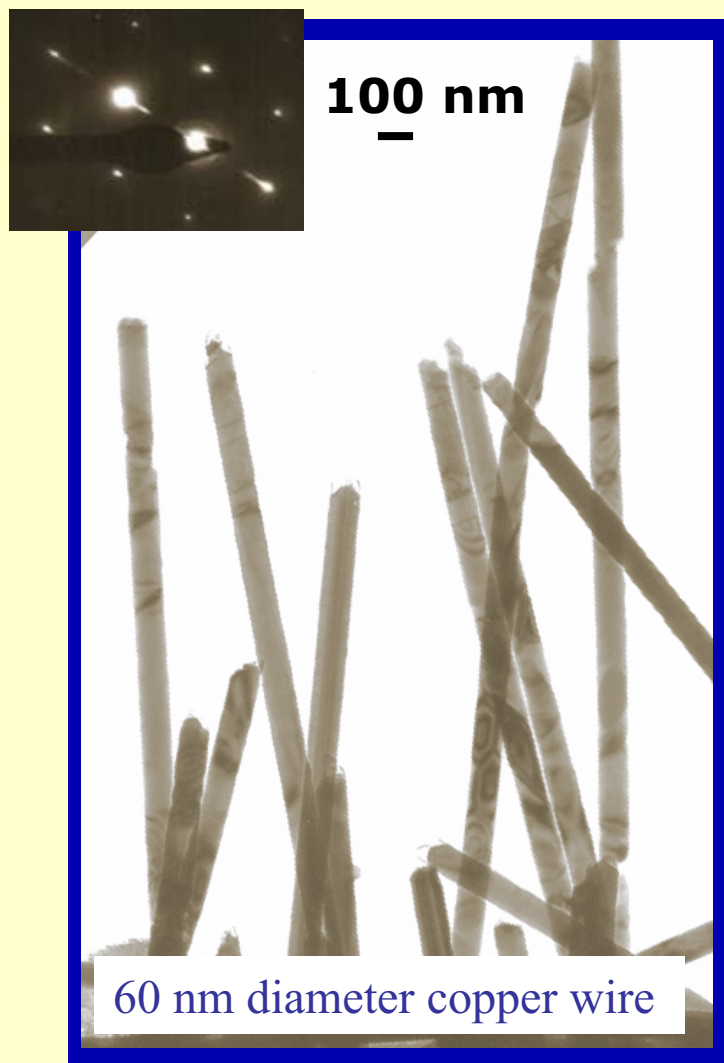
temperature  
over-voltage  
electrolyte



crystallinity

- ✓  $T = 50^{\circ}\text{C}$  &  $j < 100\text{ mA/cm}^2$ : single-crystalline
- ✓  $T = 25^{\circ}\text{C}$  &  $j > 100\text{ mA/cm}^2$ : poly-crystalline

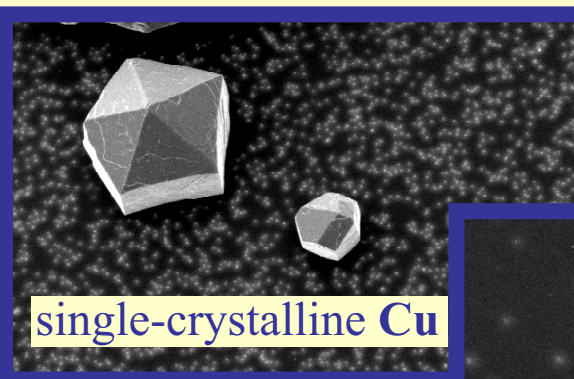
# Single-crystalline nanowires



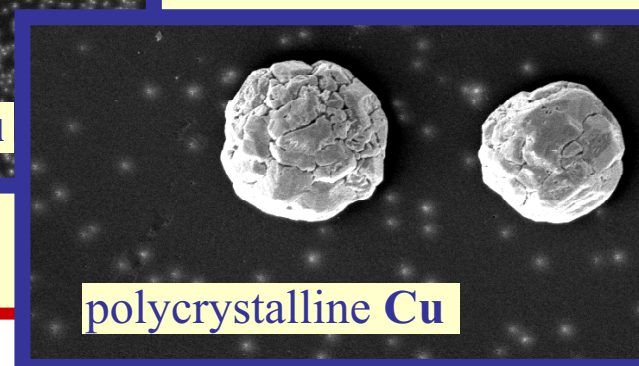
Toimil, PhD thesis, Heidelberg (2001)

low over-voltage & high temperature

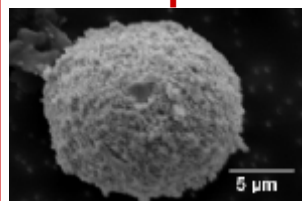
high crystallinity



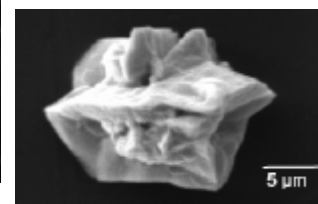
different cap morphology



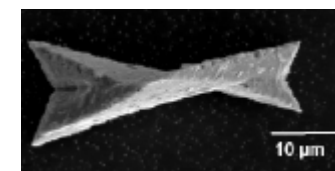
Bi caps



-40 mV, RT

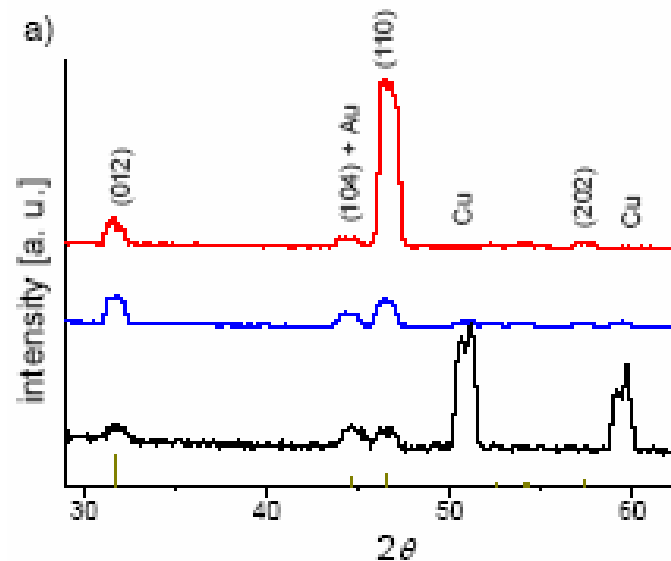


-40 mV, 60°C



-20 mV, 60°C

# Growth of textured nanowires



depends on deposition conditions

texture coefficient

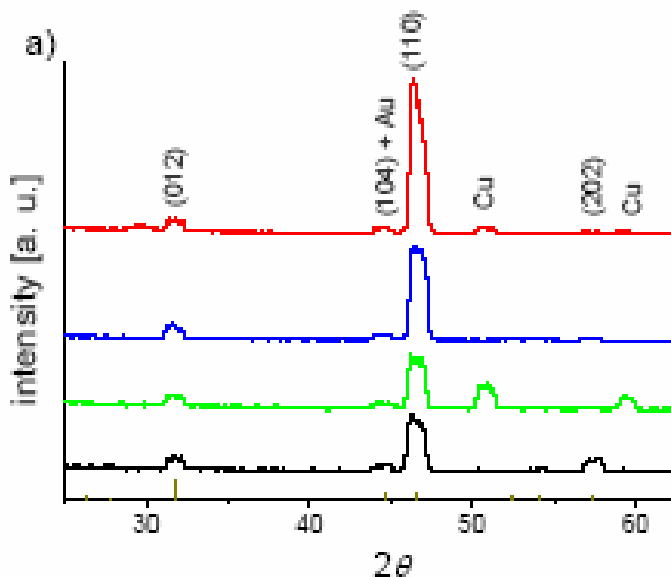
-20 mV, 60°C TC(110) = 4.2

-20 mV, 50°C TC(110) = 1.8

-30 mV, 60°C TC(110) = 1.3

powder sample

Bi wires  
 $\varnothing$  80 – 100  
 nm



depends on wire diameter

texture coefficient

40 nm TC(110) = 4.5

80 nm TC(110) = 4.2

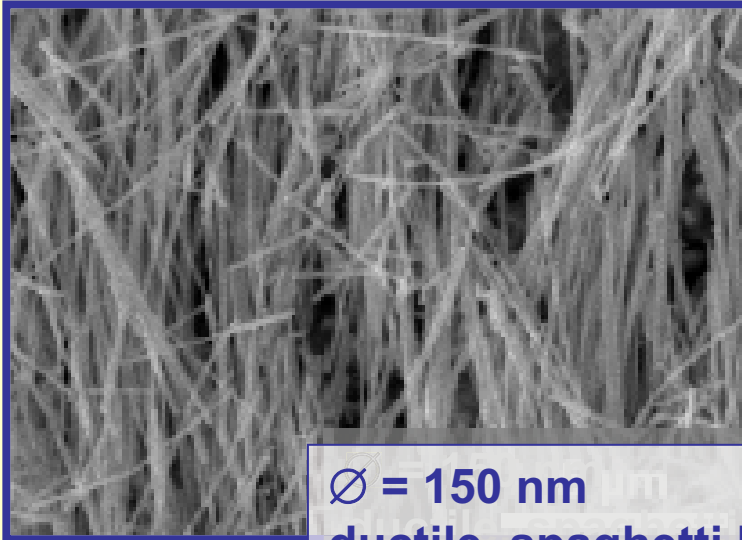
120 nm TC(110) = 3.8

160 nm TC(110) = 2.8

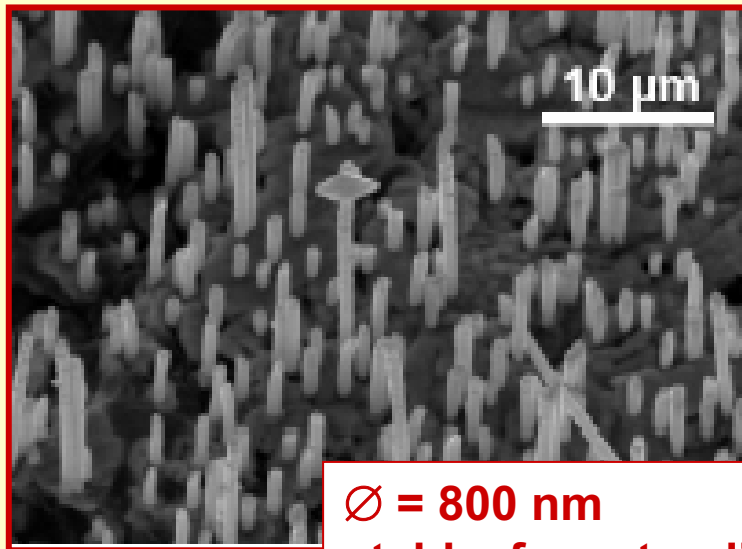
deposition  
 -20 mV, 60°C



# nanowires as cold field emitters



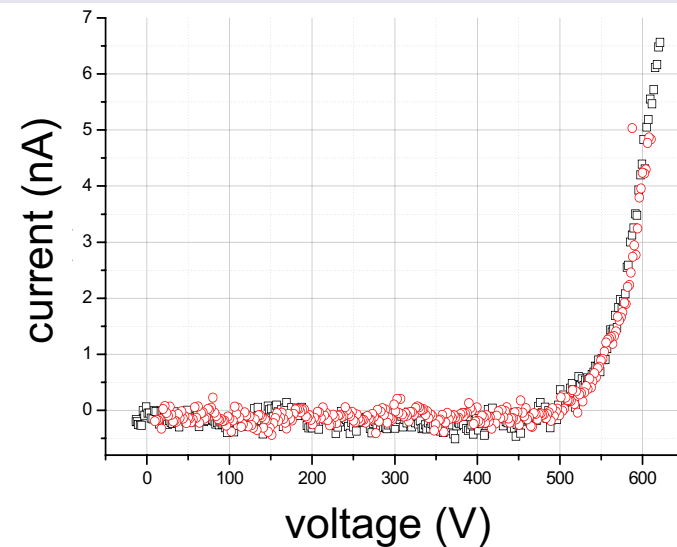
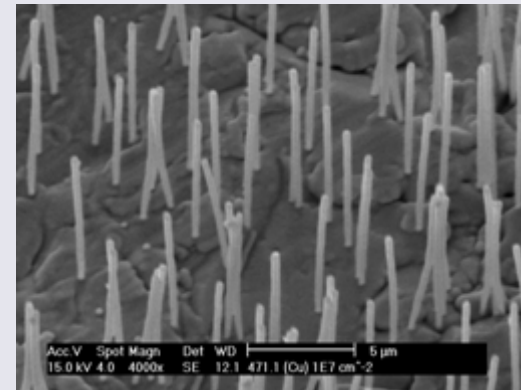
$\varnothing = 150 \text{ nm}$   
ductile, spaghetti like



$\varnothing = 800 \text{ nm}$   
stable, free standing

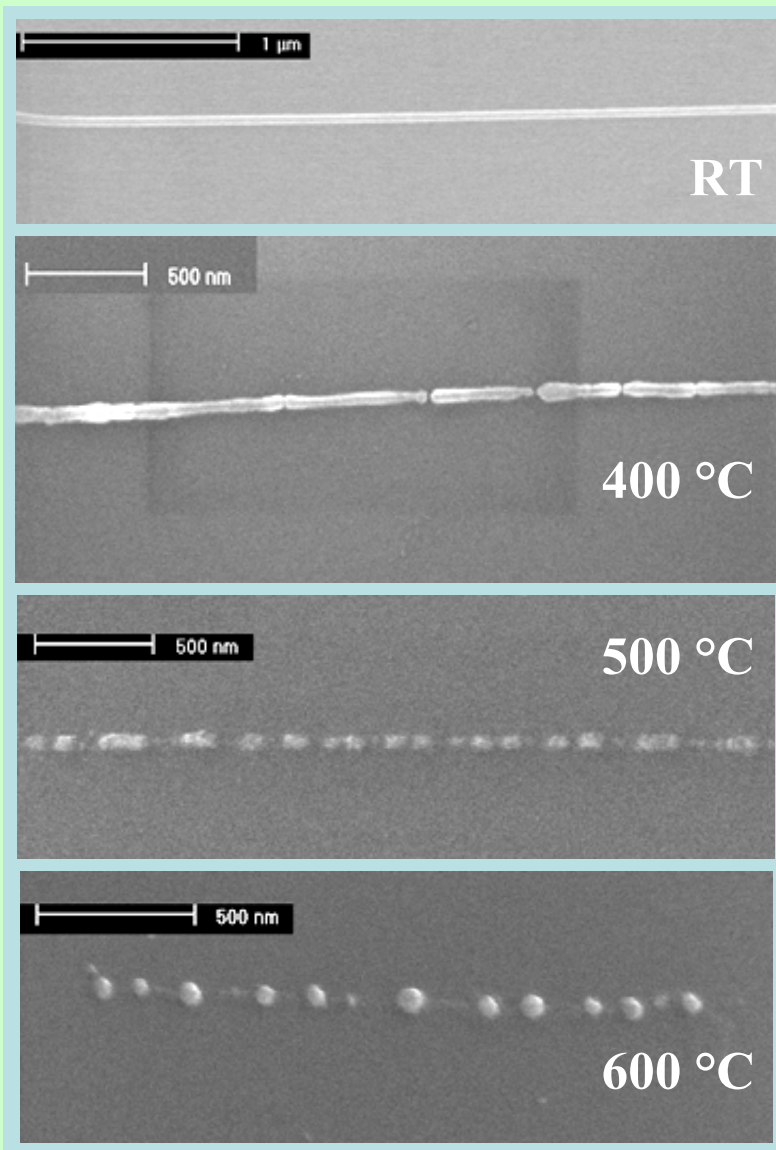
Cornelius PhD thesis, Heidelberg (2006)

## 'cold' field emitters



Maurer et al NIMB 245 (2006)

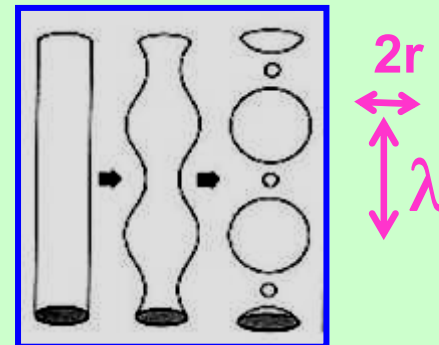
# Thermal stability of Cu nanowires



30-nm Cu nanowire  
on SiO<sub>2</sub> substrate  
annealed in vacuum, 30 min

## Rayleigh Instability

- Liquid cylinder  $\rightarrow$  spherical droplets
- Surface decrease lowers energy for  $\lambda > 2\pi r$
- For solid cylinders with radius  $r$  under surface diffusion:  
 $\lambda = 8.89r$  and  $d_s = 3.78r$

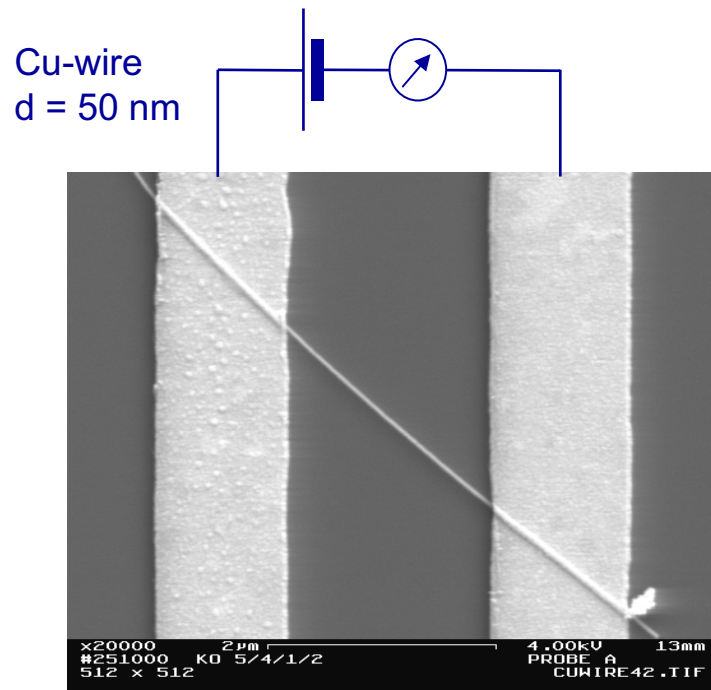


$$T_{\text{fragm}}(400^\circ\text{C}) \ll T_{\text{melt}}(1083^\circ\text{C})$$

Toimil-Molares et al., APL 85 (2004)

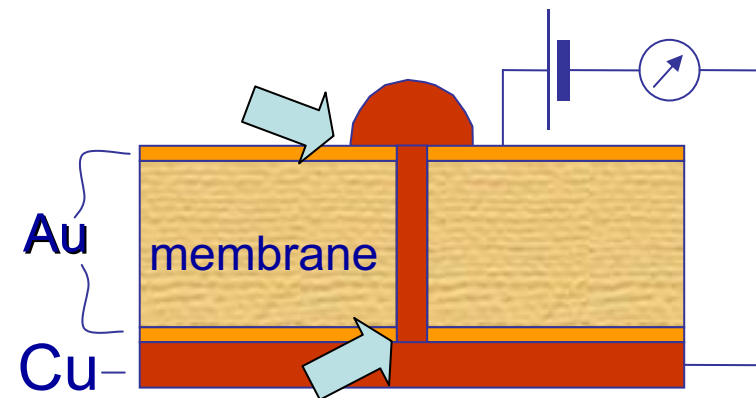
# electric transport properties of nanowires

## lithographic contacts



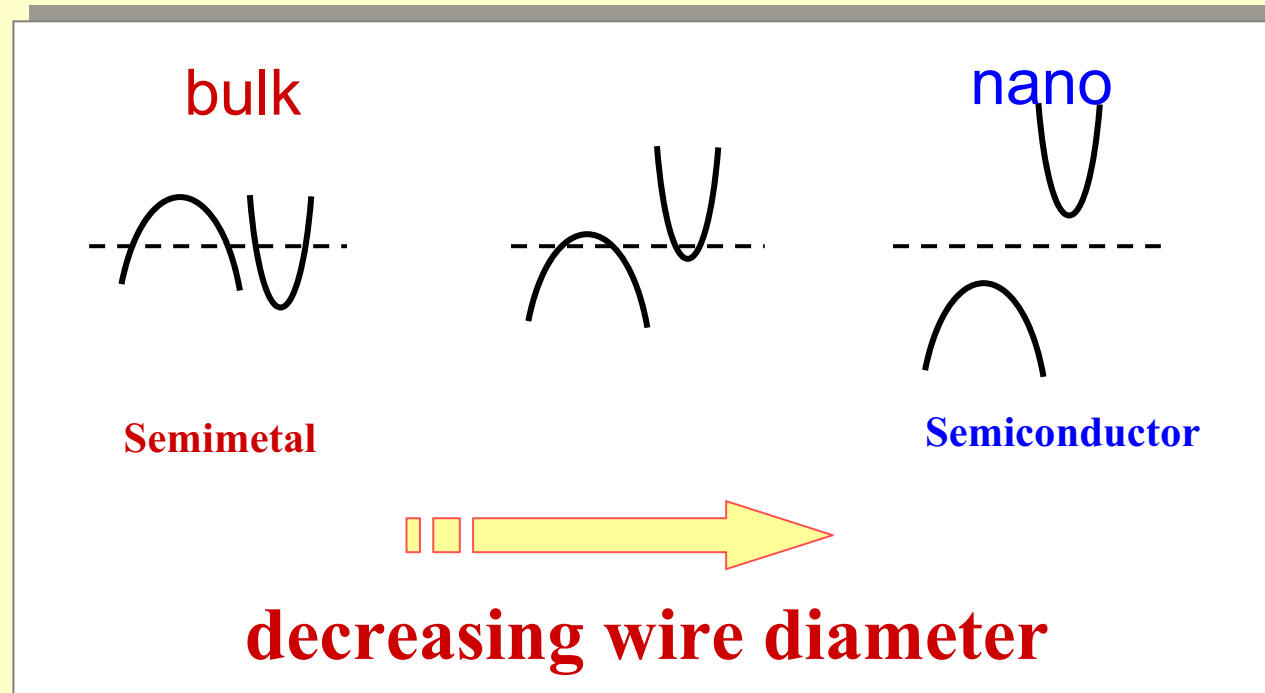
Toimil et al., APL 82 (2003) 2139

## selfdefined contacts



Enculescu et al., Appl. Phys. A, 77 (2003) 751

# Material: Bismuth



**Bulk Bi**  
conduction band overlaps with  
the valence band by 38 meV

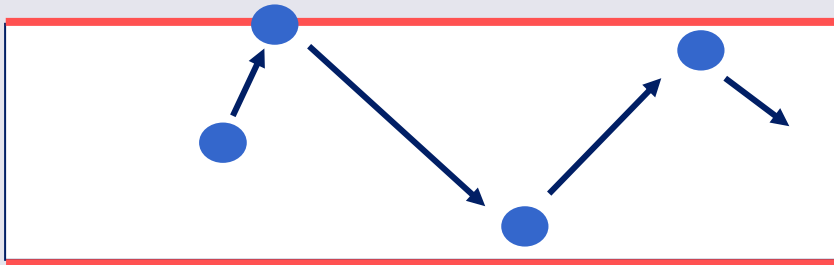
**Bi nanowires (~50 nm)**  
transition to semiconductor  
due to quantum confinement

# Surface & Grain boundary scattering

If the diameter of the wire  $\sim$  electron mean free path  $\lambda$ , additional scattering processes come into play

## Surface scattering

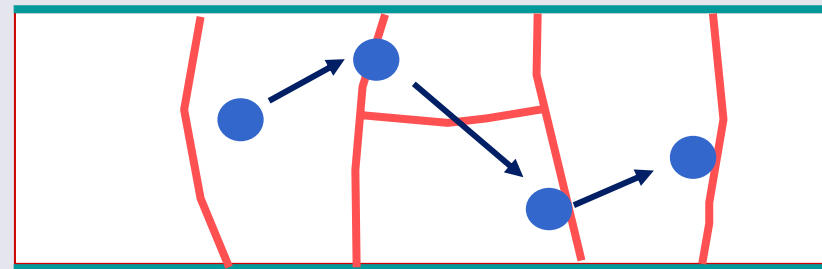
Dingle et al., Proc. R. Soc. A 201, 545 (1950)



$$\frac{\rho}{\rho_0} = f\left(\frac{D_{\text{wire}}}{\lambda}\right)$$

## Grain boundary scattering

Mayadas et al., Phys. Rev. B 1, 1382 (1970)

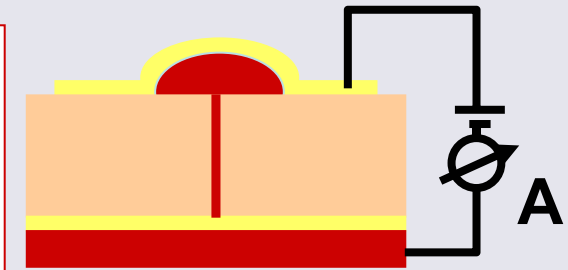
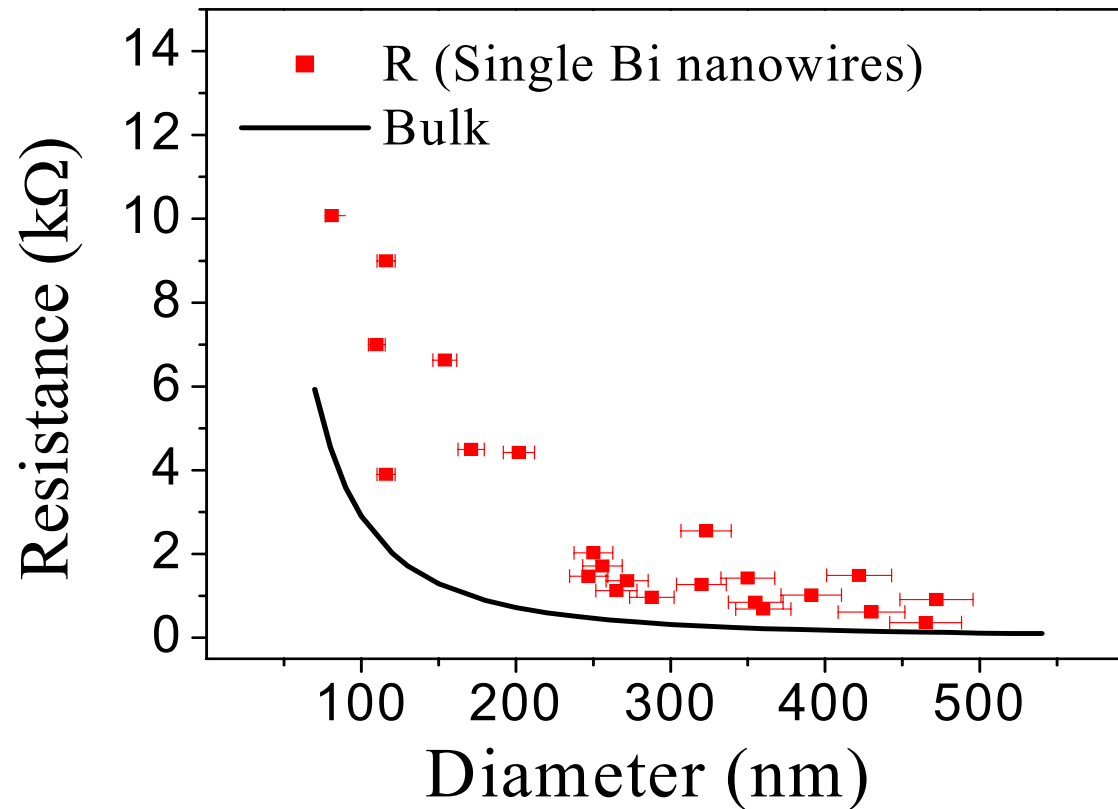


$$\frac{\rho}{\rho_0} = f\left(\frac{\lambda}{d} \frac{R}{1-R}\right)$$

$d$  = mean grain size

$R$  = reflexion coefficient

# resistance of single Bi nanowires



$T = 50\text{ }^{\circ}\text{C}$   
 $U = 20 - 40\text{ mV}$

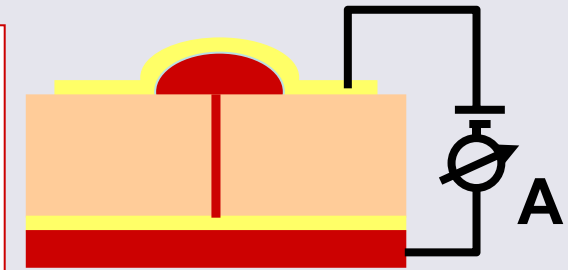
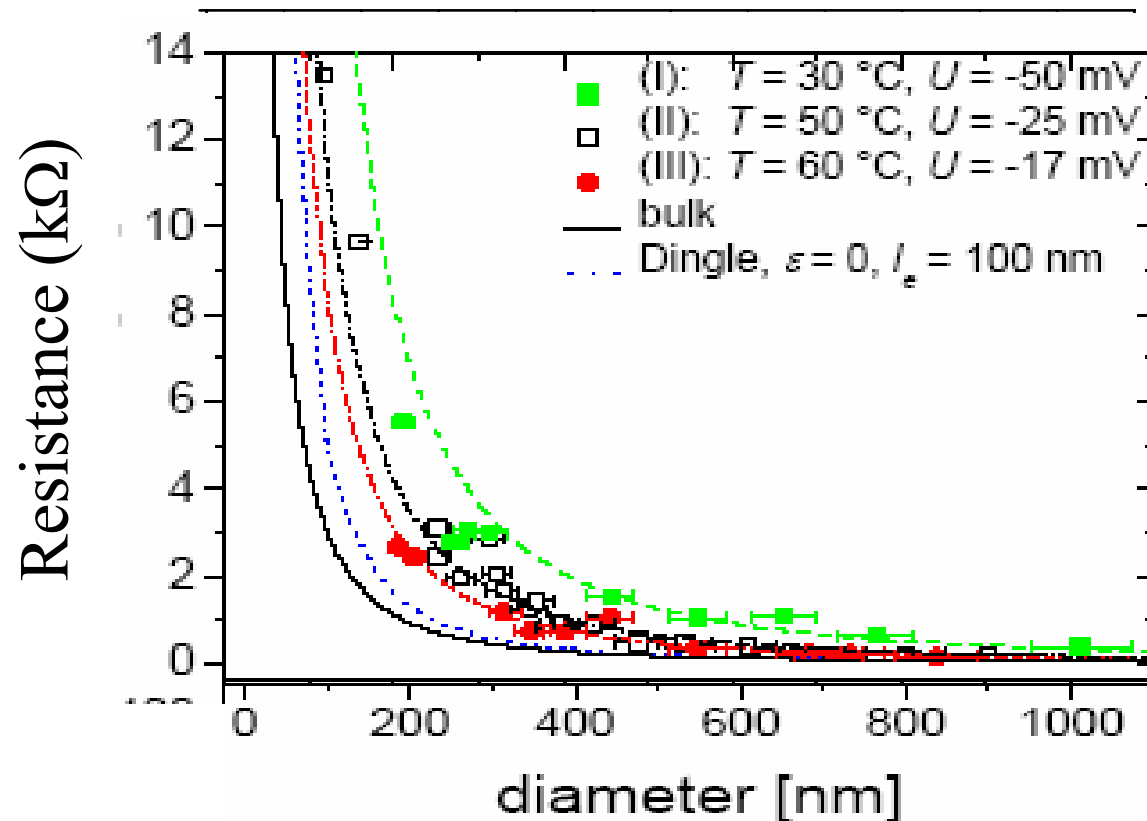
different  
crystallinity

different grain  
boundary scattering

- ✓ resistance values higher than expected for bulk resistivity
- ✓ different resistances for wires of similar diameter



# resistance of single Bi nanowires



$T = 50\text{ °C}$   
 $U = 20 - 40\text{ mV}$

different  
crystallinity

different grain  
boundary scattering

- ✓ resistance values higher than expected for bulk resistivity
- ✓ different resistances for wires of similar diameter
- ✓ resistance depends on crystallinity

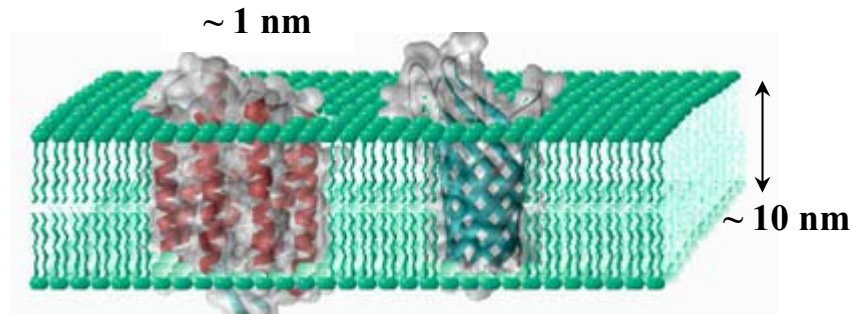
# Applications of nanopores



etched ion track  
in polymer

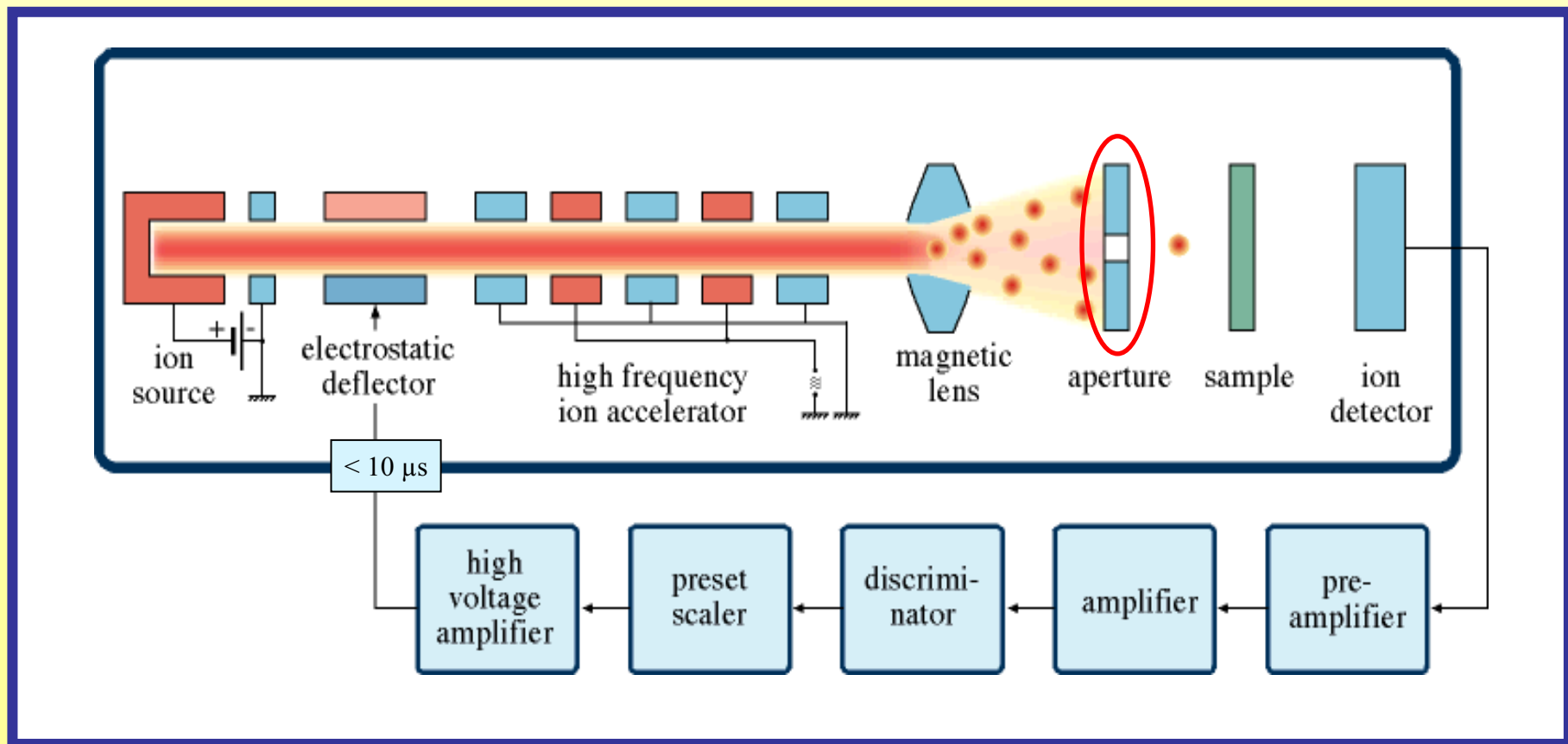
- biosensors
  - DNA detection
  - synthetic model pores
- control of pore size and shape  
less fragile

Bio-pore ( $\alpha$ -hemolysin)

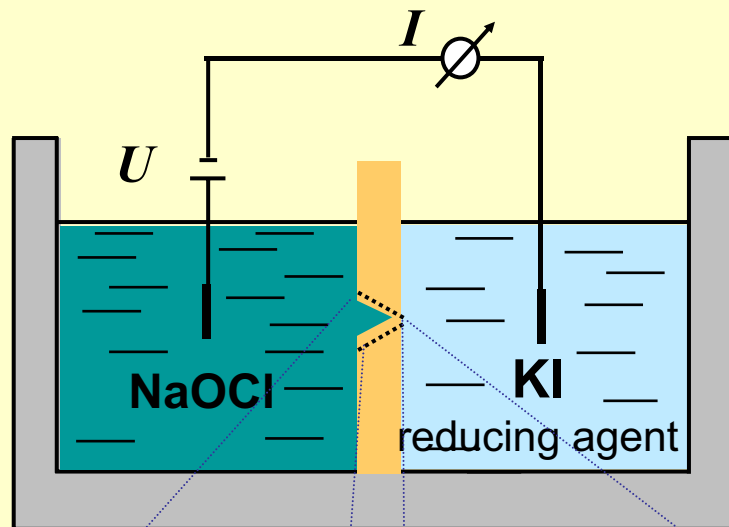


*Science* **175** (23) (1972) 720

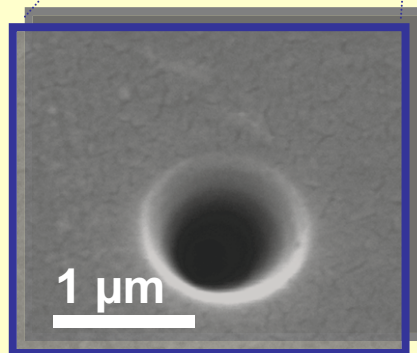
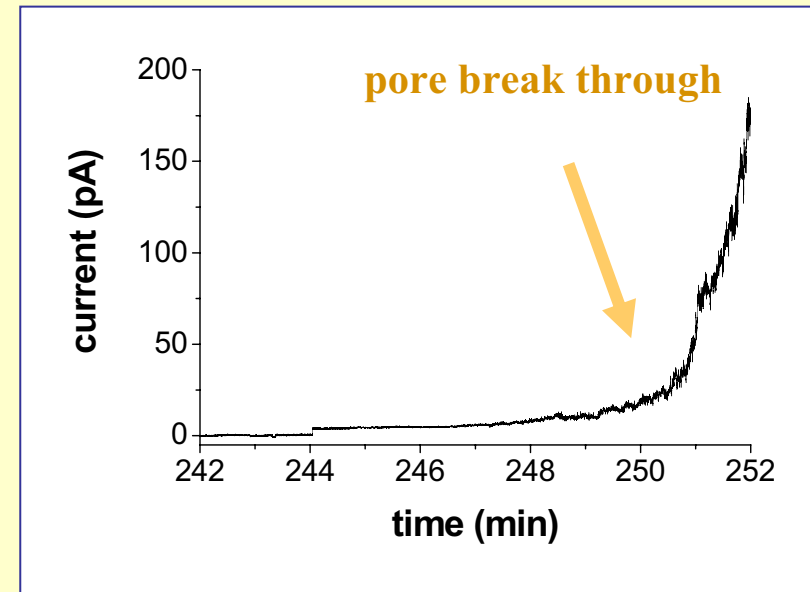
# Single ion irradiation



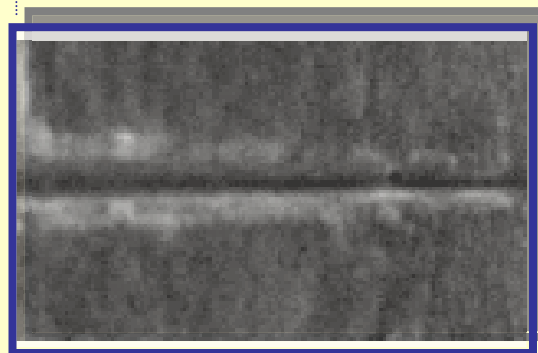
# Single nanopores by electro-stopping



**Kapton:etch stop:**  $\text{OCl}^- + 2 \text{H}^+ + 2 \text{I}^- \rightarrow \text{I}_2 + \text{Cl}^- + \text{H}_2\text{O}$



large opening



small opening

$$d \approx 2 \text{ nm}$$

$$R = 4 L / \pi \kappa D d$$

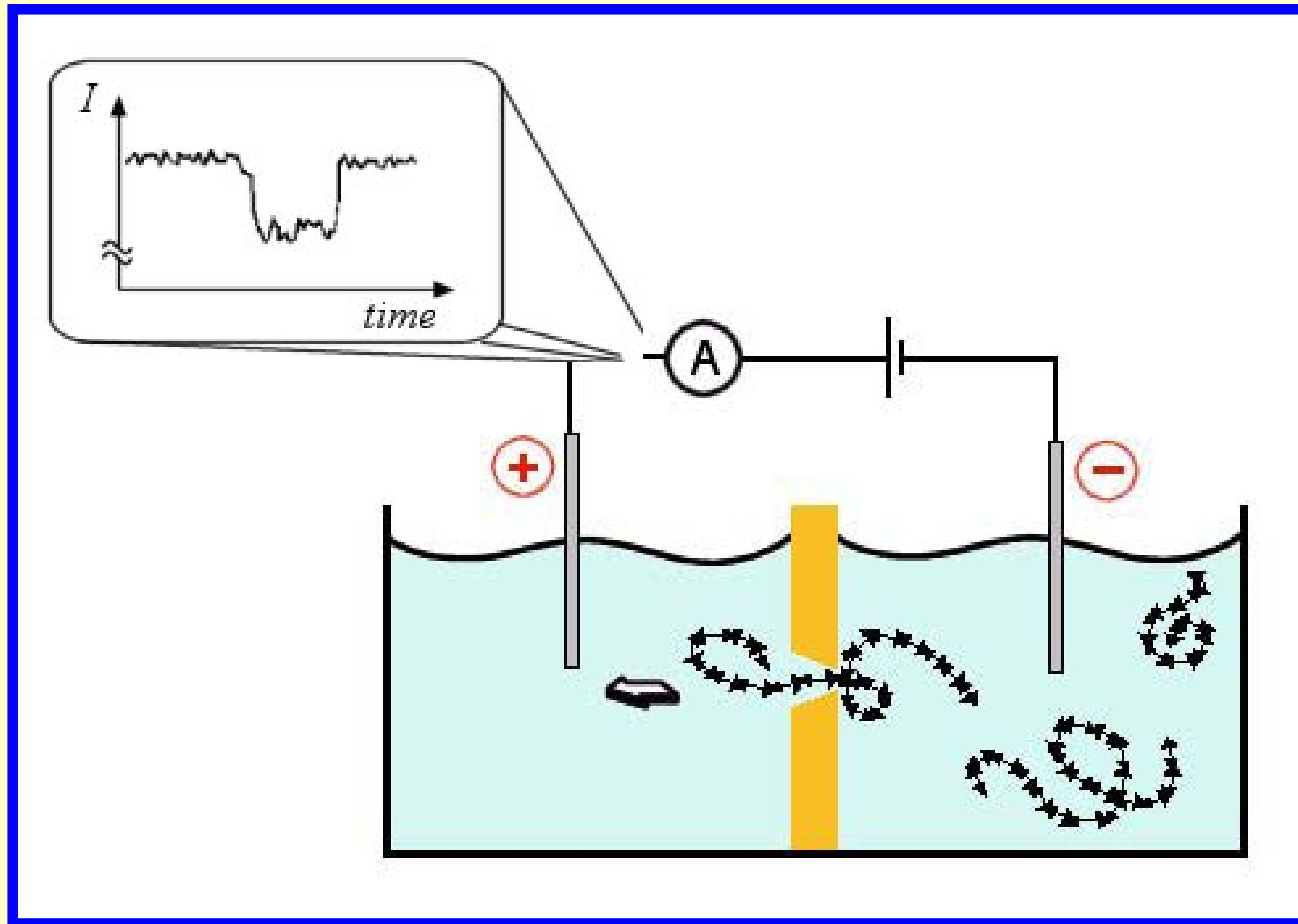
$R$  resistance

$\kappa$  conductivity of KCl

$L$  length of the pore

Siwy et al., Appl. Phys. A 76 (2003)

# Single nanopores as bio-sensors

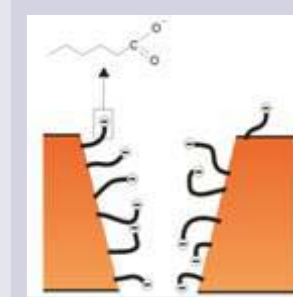


Mara et al., Nano Lett. 4 (2004) 497

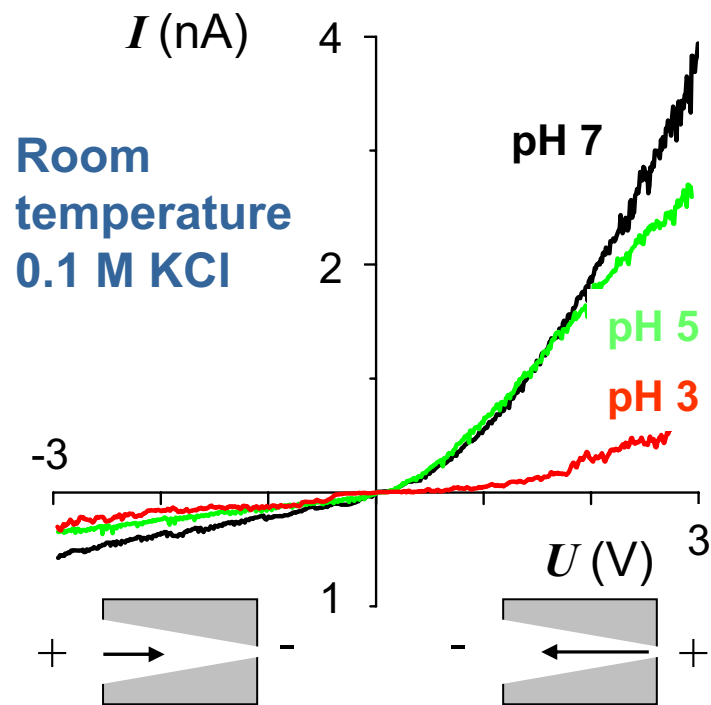
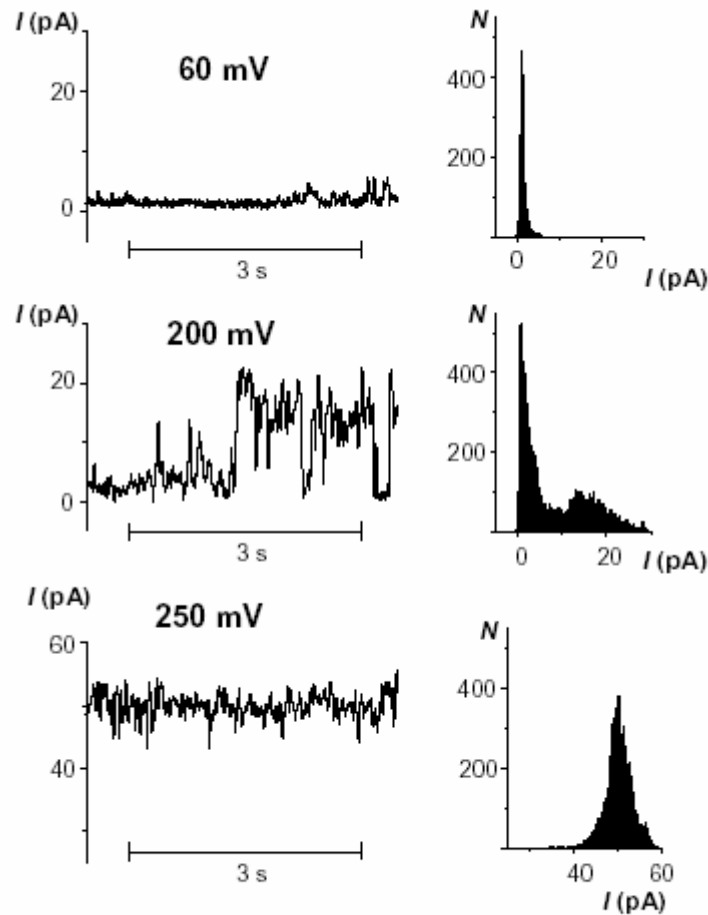
Schiedt et al., NIMB 236 (2005) 109

## ... in the case of single pores in PET ...

Ion currents also switches between discrete levels



Ion currents are also rectified



Cervera et al. Europhys. Lett., **71** (2005) 35  
J. Chem. Phys. **124** (2006) 104706

# Conclusions

- Energetic ions produce tracks of few nanometers in diameter and high aspect ratio ( $\gg 1000$ )
- Track etching in insulators (e.g., polymers, mica  $\text{SiO}_2$ ) allows the controlled production of nanoporous membranes
- Combination with micro-mechanical systems, lithography and Si technology possible
- Ion track membranes most suitable as template for fabrication of nanowires (electrical, thermal, structural etc. properties)
- Single nanopores suitable as model for bio-pores and as biosensors